

**Micro-RDC**

Microelectronics Research Development Corporation

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# **RHBD Standard Cell Library Approach**

**Presented by  
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# Key Technical Personnel – Design Hardening

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## □ Dave Mavis – Chief Scientist Micro-RDC

- B.S. Physics, University of Wisconsin
- Ph.D. Nuclear Physics, Stanford University
- Post Doctoral Fellow, Stanford University; Faculty, University of Wisconsin; Ion Source Design Consultant, Sentec, Geneva Switzerland; MRI Consultant, USFRIL, South San Francisco, CA; Technical Staff, Mission Research, Albuquerque, NM
- Founder Micro-RDC

## □ Relevant Experience

- Assisted numerous vendors (BAE, Honeywell, TI, Boeing, & others) to harden, characterize, and model product offerings
- Led commercial and Government contract efforts in device physics modeling; SEE circuit analyses; device parameter extraction; thermal management; CAD tool development; RHBD cell library, SRAM, FPGA, and Structured ASIC design; novel test method and data reduction technique development

# Key Technical Personnel – Radiation Testing

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## □ Paul Eaton – Chief Engineer Micro-RDC

- B.S. Texas Tech University
- M.S. Texas Tech University
- Technical Staff, Sandia National Laboratory, Albuquerque; Technical Staff, Mission Research, Albuquerque, NM
- Founder Micro-RDC

## □ Recent Activities

- Key role in SEE circuit analyses; structured ASIC qualification vehicle design; various circuit verifications and characterizations
- Led commercial and Government contract efforts in DSET characterization circuit design, simulation, layout, packaging, and testing; FPGA-based generic test board design; heavy-ion data acquisition and data analysis software development

# Several Key Library Considerations

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- ❑ **TID**
    - Not expected to be a factor for 300 kRad(Si) requirement
  
  - ❑ **SEL**
    - Should not be an issue, especially if fabricated on epi
  
  - ❑ **SEU**
    - Latches and SRAM require circuit mitigation techniques
  
  - ❑ **DSET**
    - Transient filtering needed in data, clock, and control
  
  - ❑ **Library timing characterization**
    - Need, especially for DSET, realistic SPICE current sources
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# RHBD Library Development Approach

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- ❑ **Baseline the fabrication process**
    - Determine TID and SEL hardness levels through test (and SEU/DSET to whatever extent possible) with existing structures and circuits
    - Audit library layout for potential problems (e.g. well/substrate contacts)
  
  - ❑ **Fabricate/test radiation environment specific characterization chip**
    - Appropriate circuits for characterizing SEU baseline error rates without mitigation (e.g. with redundancy and/or EDAC)
    - Appropriate circuits for quantifying DSET pulse width distributions in the combinatorial logic (to establish required filtering delays)
    - Appropriate structures for determining required critical node spacing (primarily to bound EDAC scrubbing rates)
  
  - ❑ **Finish using conventional library development procedures**
    - Modify old layouts and generate new layouts as required
    - Generate the various library views, with only timing impacted by RHBD
    - Final heavy-ion testing, Milli-Beam to supplement broad-beam
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# Presentation Overview

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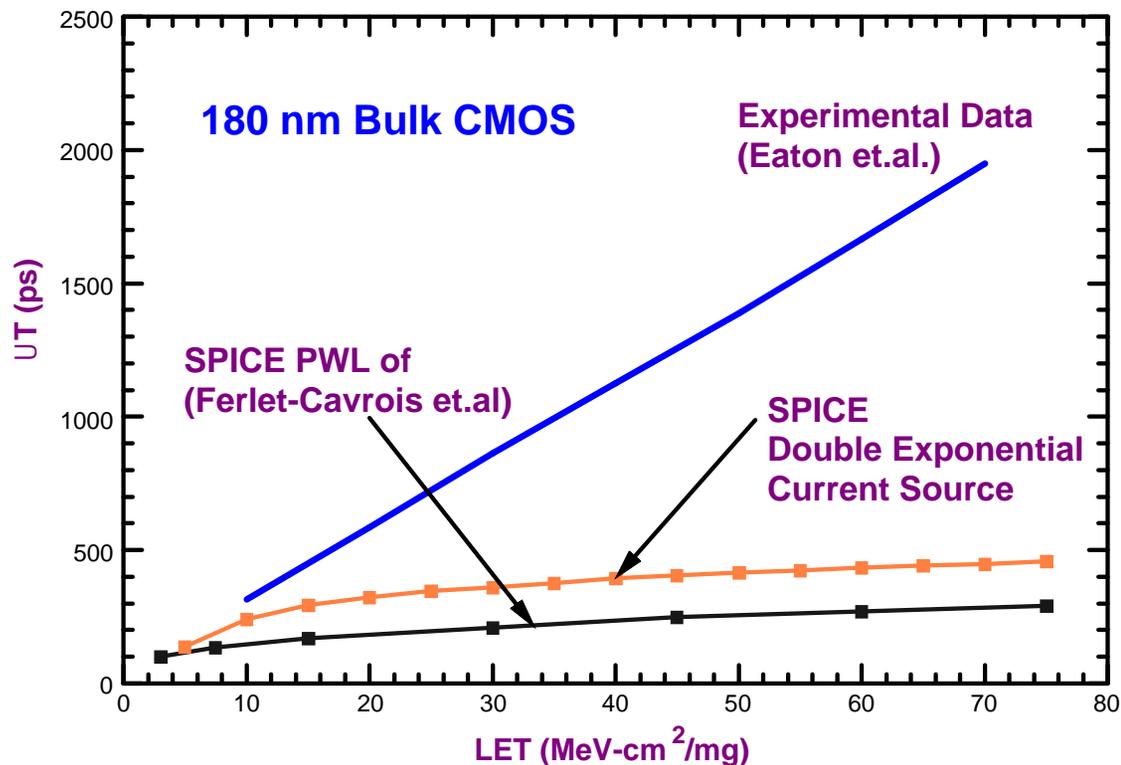


- ❑ **Quick description of our Equivalent Collection Model (ECM)**
    - Described fully in our 2007 IRPS invited presentation
    - Presently only available at Micro-RDC
  
  - ❑ **Circuit redundancy issues for latch and SRAM designs**
    - Latch critical node and SRAM bit separations are key
    - Much learned from our DARPA RHBD design & characterization efforts
    - Area must be traded for hardness
  
  - ❑ **DSET transient filtering**
    - Newly discovered pitfalls need to be addressed
    - The "Temporal Filtering Latch" surmounts several intractable problems recently encountered with DICE-based and TMR-based latch designs (as described in our 2002 IRPS invited presentation)
    - Speed must be traded for hardness irrespective of which filtering approach is taken
-

# Realistic DSET Modeling in SPICE



- ❑ Transient widths were much larger than previously thought
- ❑ Current source waveforms could not account for the data
- ❑ Circuit response was missing from the simulation model



# Salient Features of the Model



- ❑ **Collection dynamics must be established by circuit response**
  - Currents must decrease as voltages collapse (reduced E fields)
  - Pulse broadening will occur naturally (longer times will be needed to clear a fixed charge from the substrate)

- ❑ **The ECM reflects these dynamics**

- Captures the effects of node voltage collapse
- Variational calculus to solve integral equation with variable limits:

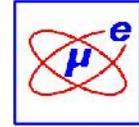
$$\text{Solve for } I(t): \int_0^{t(s)} I(t') dt' = Q(s), \text{ given } Q(s = \infty)$$

- Note that  $I(t)$  is implicitly defined from an integral whose limit of integration varies according to the circuit response
- Exponentials are easy:

$$\text{If } I(t) = I_0 e^{-t/\dagger}, \text{ then } Q(t) = I_0 \dagger (1 - e^{-t/\dagger}), \Rightarrow I(t) = \frac{I_0 \dagger - Q(t)}{\dagger}$$

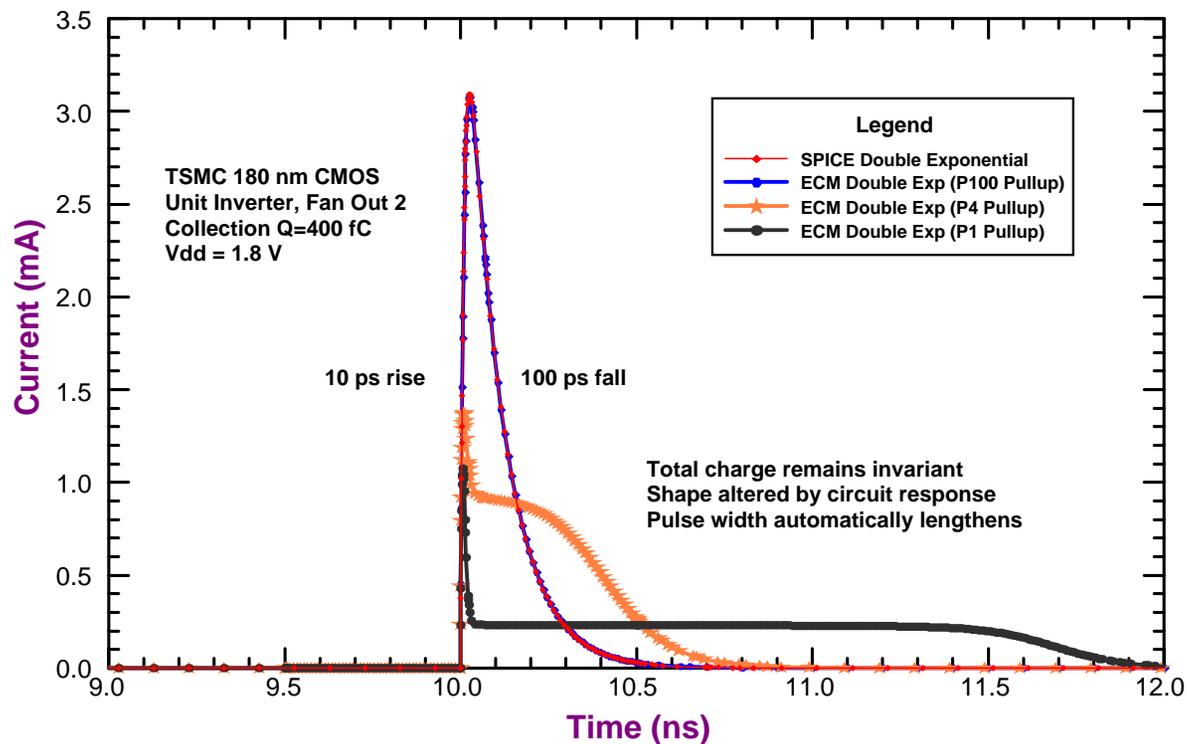
Modulate  
With  
Voltage

# ECM Currents Depend on Circuit Response



## □ Formulate an integral equation for the double exponential

- Hard rail  $\rightarrow$  reduces to SPICE waveform  $\frac{Q_{tot}}{(2-1)} \cdot (e^{-t/\tau_2} - e^{-t/\tau_1})$
- Real circuit  $\rightarrow$  pulse broadening in response to voltage collapse

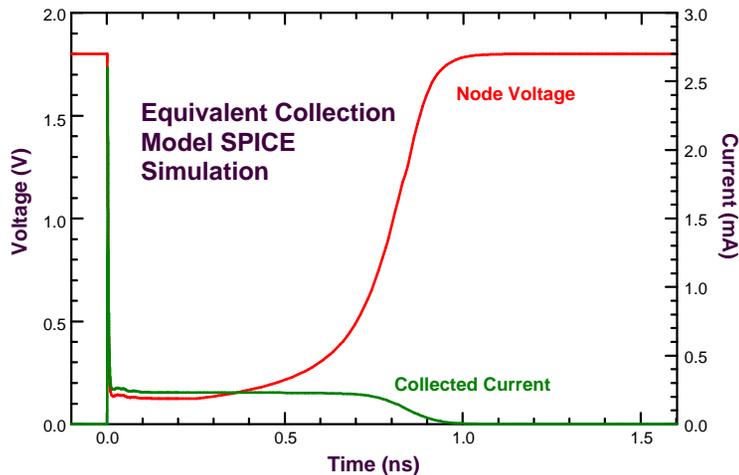
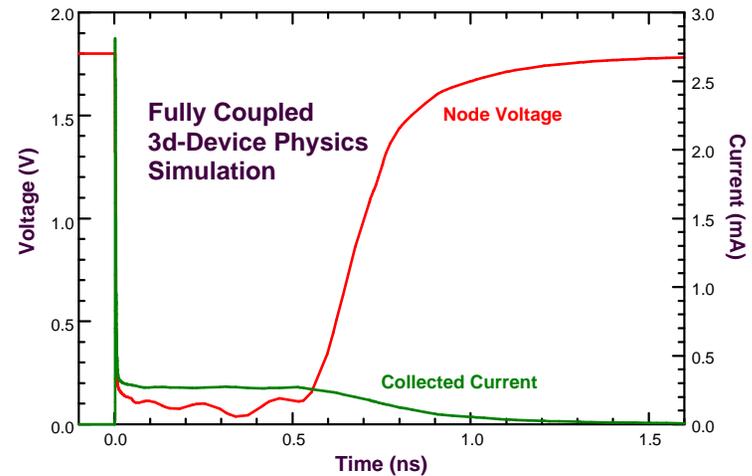


# Circuit ECM Agrees with 3d Physical Model



## CFDRC simulation results

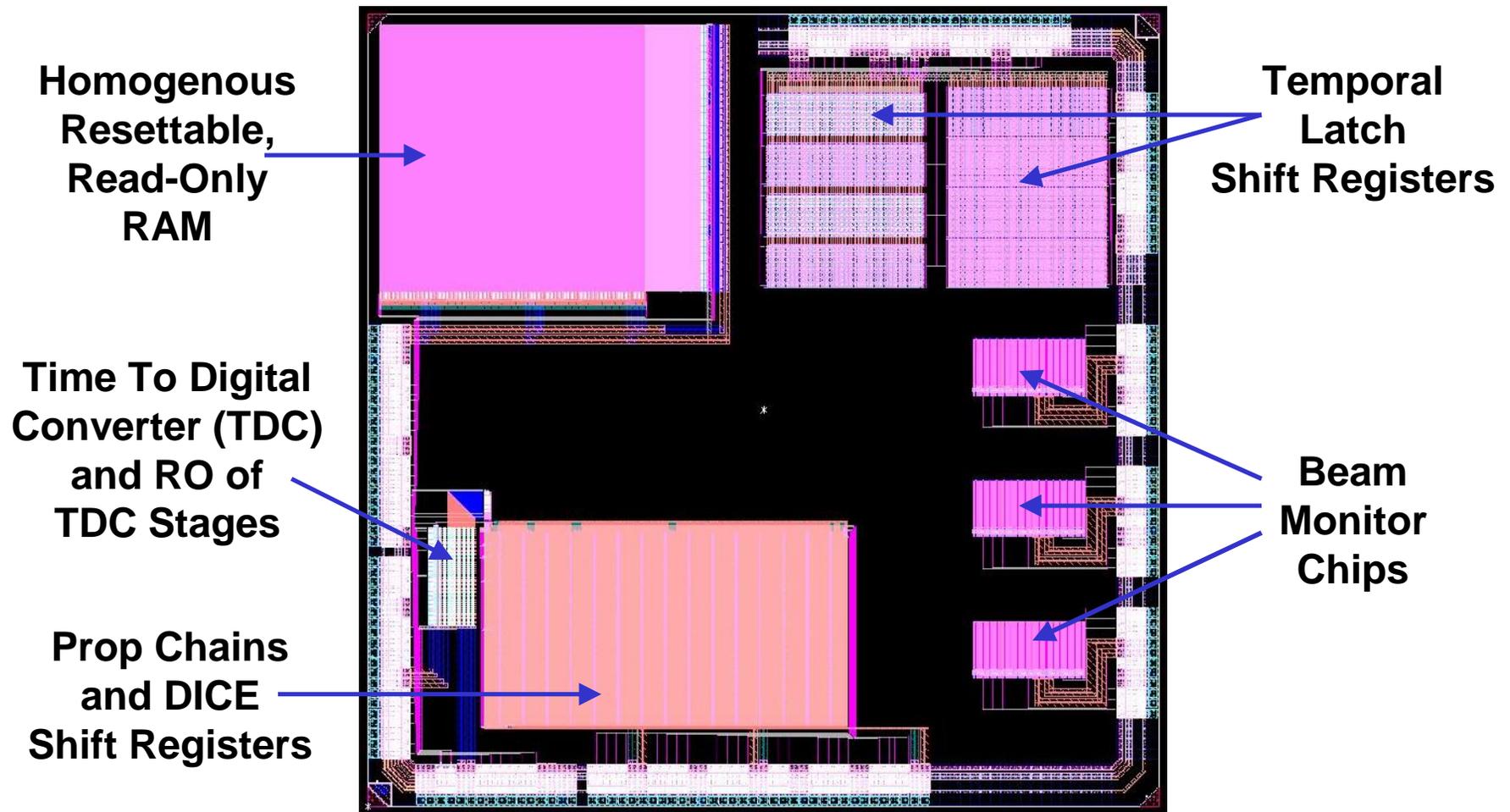
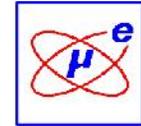
- TSMC 180 nm CMOS
- $V_{dd} = 1.8 \text{ V}$
- $\text{LET} = 20 \text{ MeV-cm}^2/\text{mg}$
- $\sim 200 \text{ fC}$  collected charge
- Final pulse width of 700 ps



## SPICE simulation with the ECM

- CFDRC inspired waveform
- 200 fC collected charge
- Excellent agreement over all times with full 3d simulations
- Collection current equilibrates with PMOS pull up, accounting for DSET pulse width

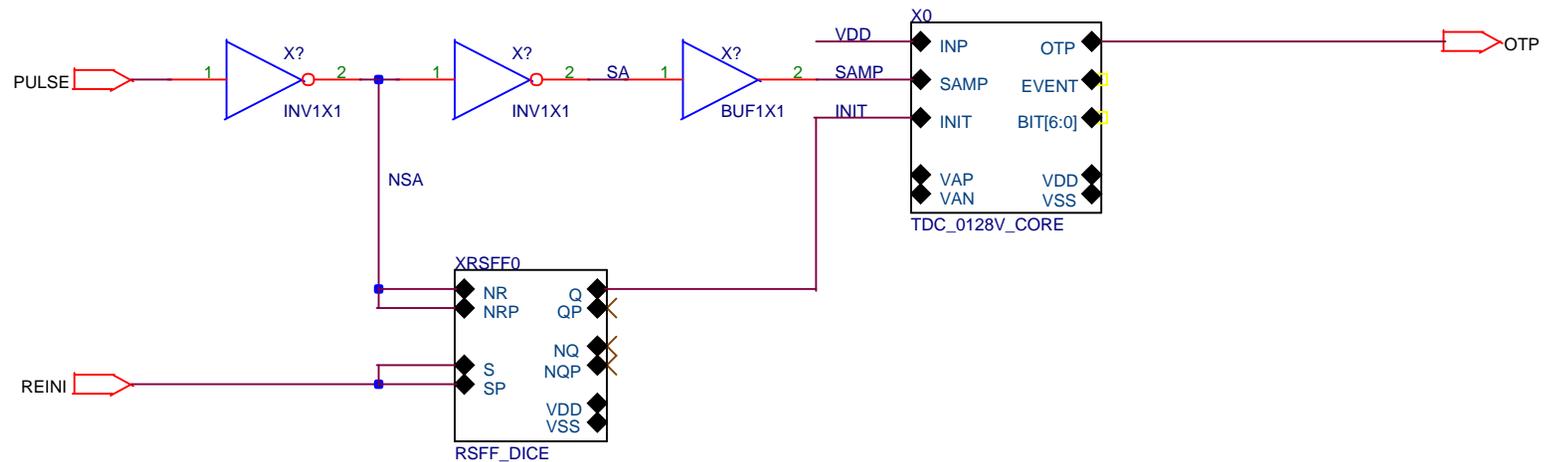
# Typical Micro-RDC Test Chip (90 nm IBM 9LP)



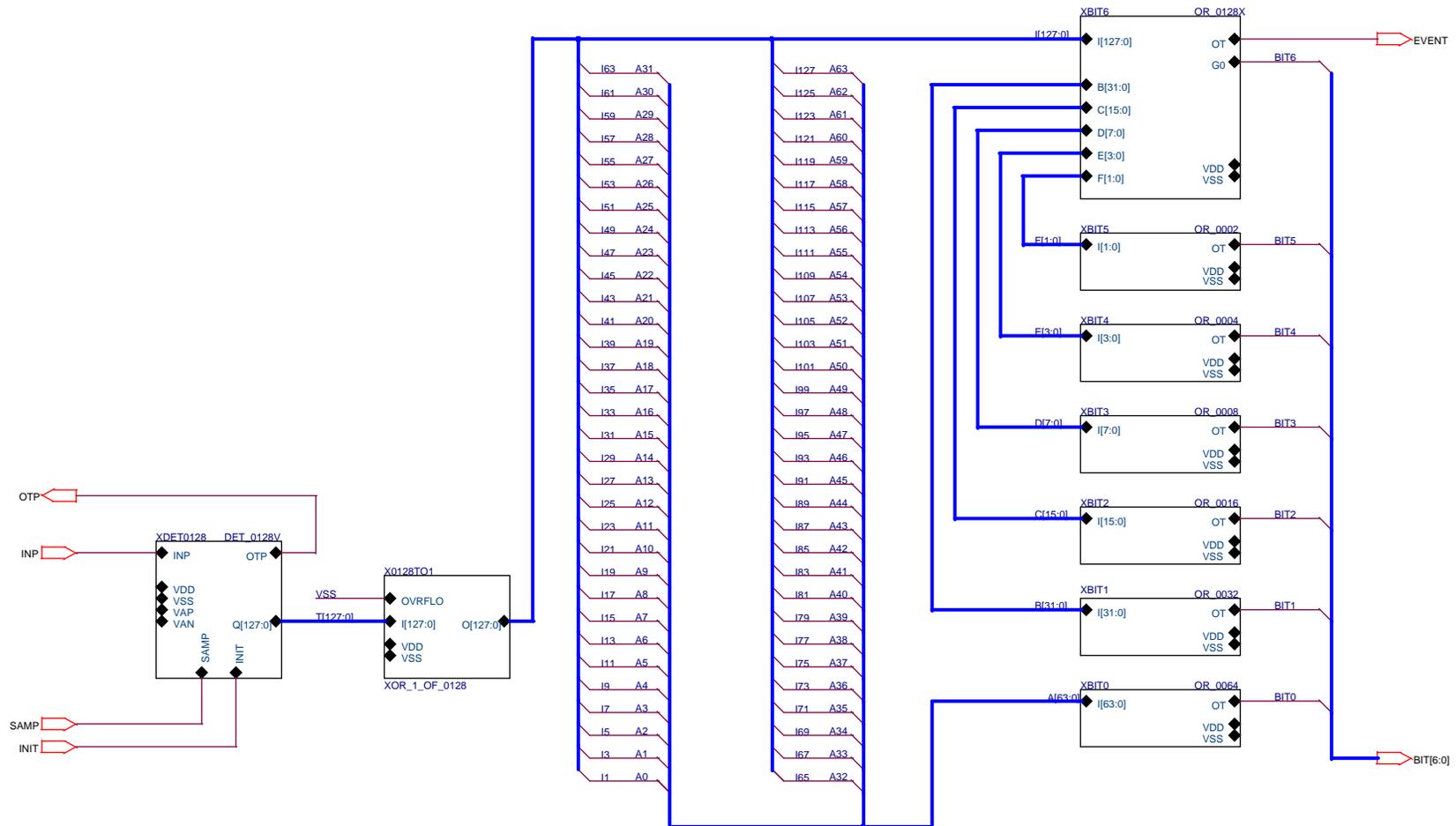
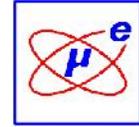
# Time to Digital Converter (TDC)



- ❑ Measure differential transient pulse width distributions
  - Gated thermometer code generator (128 stages)
  - High water "1 of N" detector
  - OR-gate-based fat-tree priority encoder (7 output bits)
- ❑ Upset hardened (1 in every  $4 \times 10^6$  data may be corrupt)
  - Generator susceptible only when processing a transient
  - DICE-based RSFF controls the processing
- ❑ Propagates an edge – not a pulse



# 128 Stage TDC Version



**128 Stage  
Code Generator**

**1-of-N  
Detect**

**Fat-Tree  
Priority Encoder**

# SEE Mitigation Methods

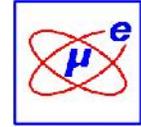
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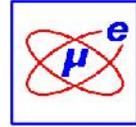
- ❑ **Well de-biasing known to cause problems**
  - 90 nm and smaller technology nodes
  - Seen in SRAM MBU measurements
  - Seen in DICE-based latch layouts
  
- ❑ **Test chip includes several shift register designs**
  - DICE-based latch with multiple n-wells
  - Temporal Latch with shared n-well
  - Temporal Latch with multiple n-wells

# DICE Latch Considerations

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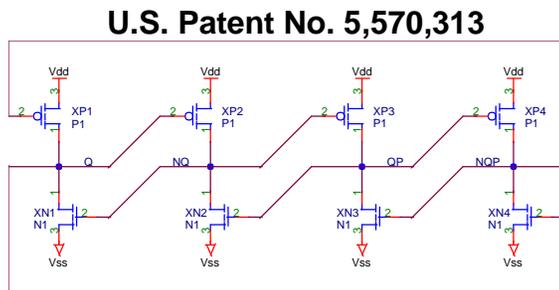


- ❑ **Gained popularity because of internal redundancy**
    - Immune to upset from a single node strike
    - Separating critical nodes thought to provide acceptable error rates
  
  - ❑ **Loosing popularity due to new radiation response mechanisms**
    - Well de-biasing makes node separation difficult
    - Separations of 10 to 20 microns not adequate in real applications
    - Susceptible to DSETs on data inputs, clock inputs, and control lines
    - Transient filtering required on each of these signals
    - Basic DICE-implementation must be correct or the guard gate itself will be a non-filterable DSET target that will cause errors
  
  - ❑ **Recommendation**
    - Use a latch that is inherently immune to transients on any node and is immune to multiple node strikes (which can actually be accomplished by replacing spatial redundancy with temporal redundancy)
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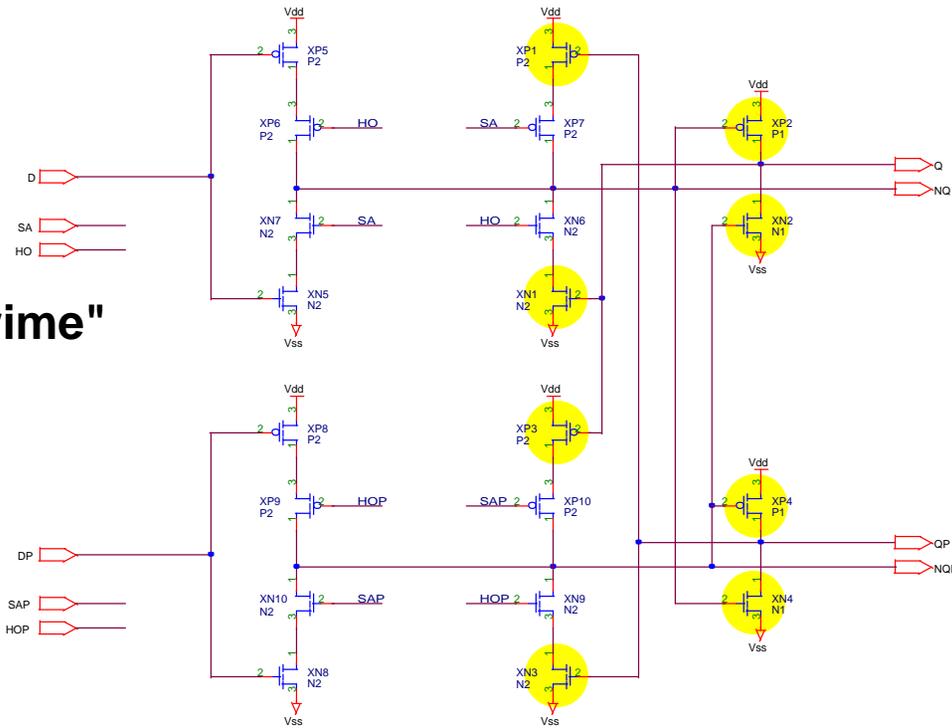
# How to Correctly Implement DICE

- By analogy, build a DITLAT from a DICE SRAM cell:



- Each signal now has a "prime"

- D and D'
- SA and SA'
- HO and HO'
- etc for any set signals
- etc for any reset signals



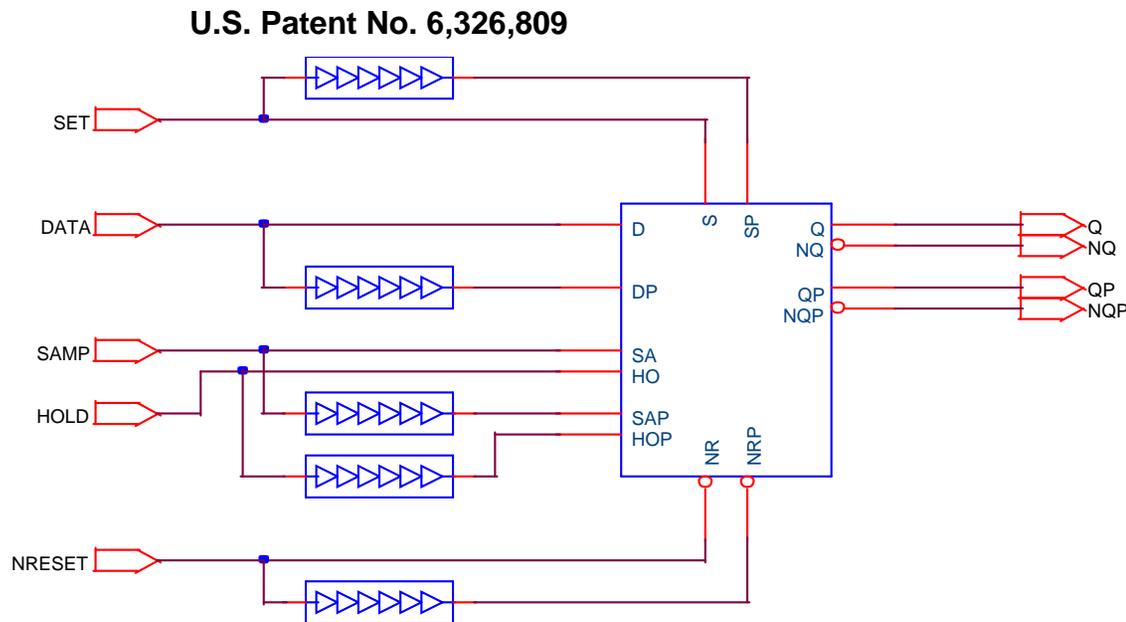
- Need to assert both a signal and its prime to invoke an operation

- This is the key for transient filtering

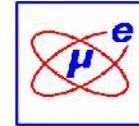
# Correct Transient Filtering on DICE Latches



- ❑ Only need to delay the "primed" signal with respect to the signal
  - Delay of UT filters transients of width UT and shorter
  - Increases latch setup and hold times by  $2UT$

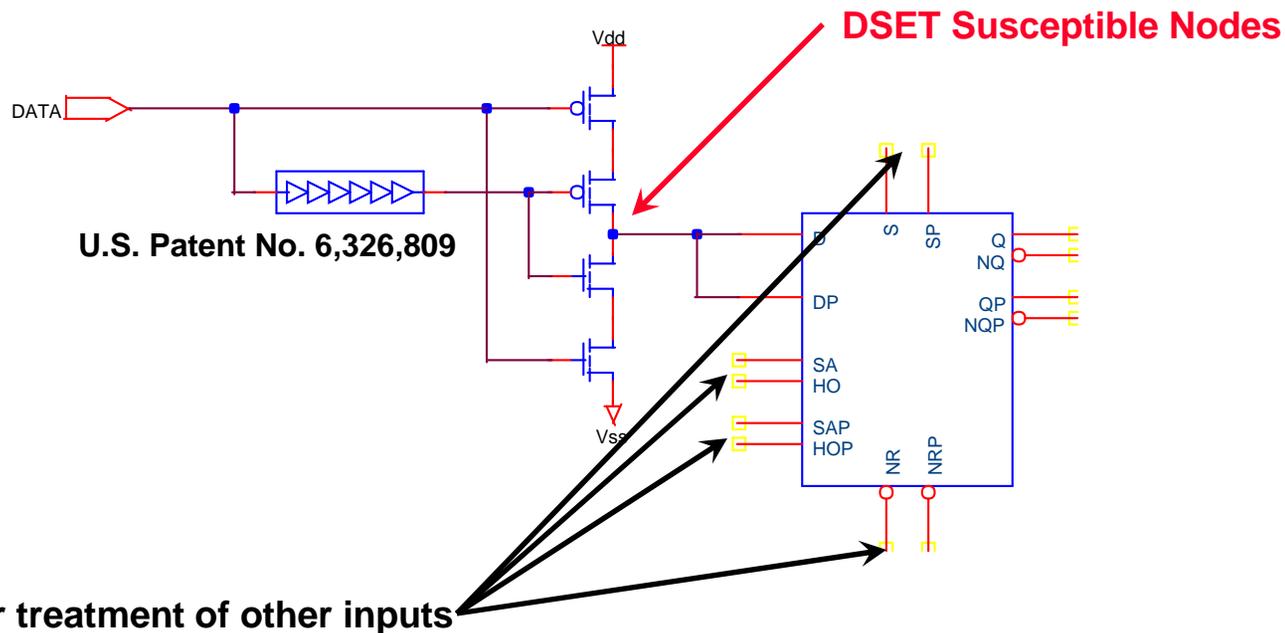


# Incorrect Transient Filtering on DICE Latches



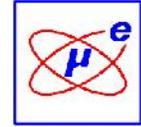
## □ Guard gate includes the filtering delay

- Again increases latch setup and hold times by  $2UT$
- Only removes transients incident on the guard gate
- Guard gate itself becomes a DSET susceptible target
- Who's guarding the guard gate???



# Requirements for Separation of Critical Nodes

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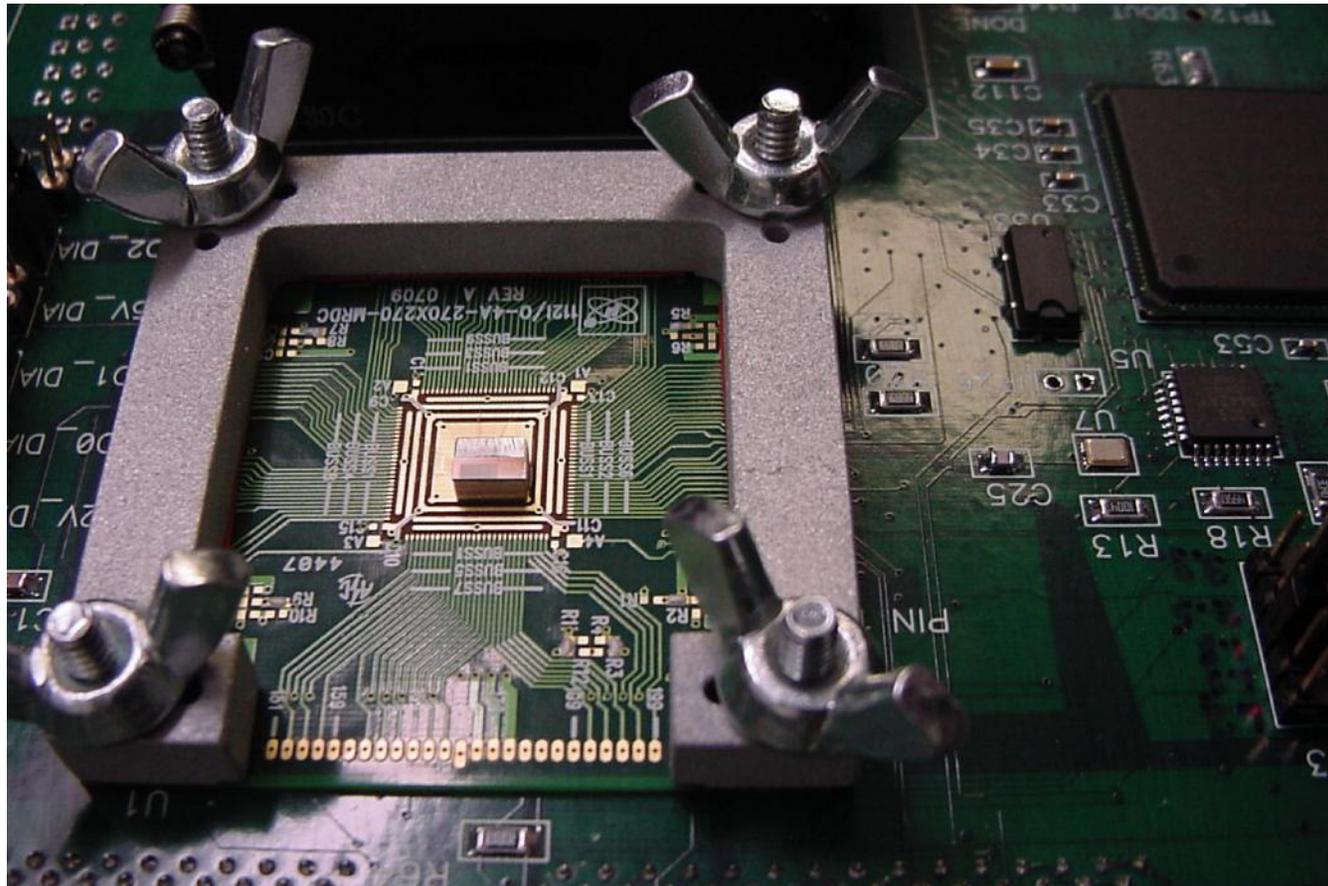


- ❑ **Initial efforts directed toward DARPA RHBD SRAM design**
    - Designed, fabricated, and packaged a special SRAM device
    - Performed true 90° heavy-ion testing (89° won't cut it)
  
  - ❑ **Results applicable to other circuit designs**
    - DICE-based latch cells
    - Older TMR approaches
  
  - ❑ **Discovered a few unexpected results**
    - Collection funneling depths not as deep as hoped
    - Shallow P+ or BOX engineered substrates not very helpful
  
  - ❑ **SOI with <50 nm Silicon thickness hoped to be the solution**
    - DARPA RHBD and DTRA RHM focusing on 45 nm and 32 nm SOI
    - Charge track diameters may negate any value gained (50 nm diameters for earth based testing, much larger for 1 GeV/nucleon Fe in space)
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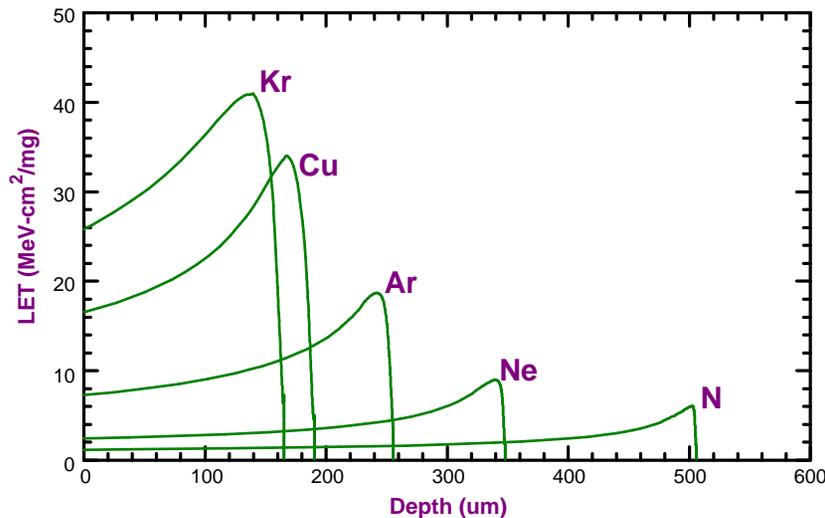
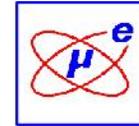
# True 90° SRAM Testing



- ❑ Specially designed IC in conjunction with novel die attach



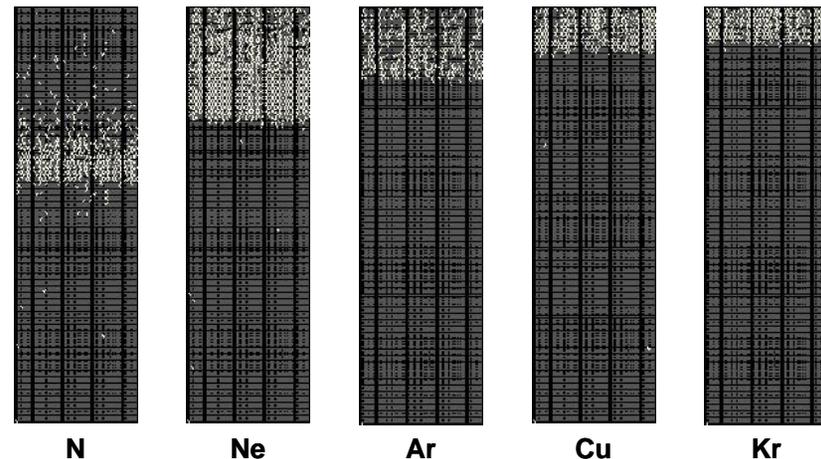
# Edge on Illumination of SRAMs



- 16 MeV/nucleon beam for maximum penetration
- Berkeley "base" and "face" angles can be accurately varied in 0.1° steps
- Measure various SEU and MBU cross sections

- Map bit error addresses to bit cell physical locations
- Edge on results agree with SRIM predictions
- Can see threshold LET effects in Nitrogen beam results

Edge of Silicon



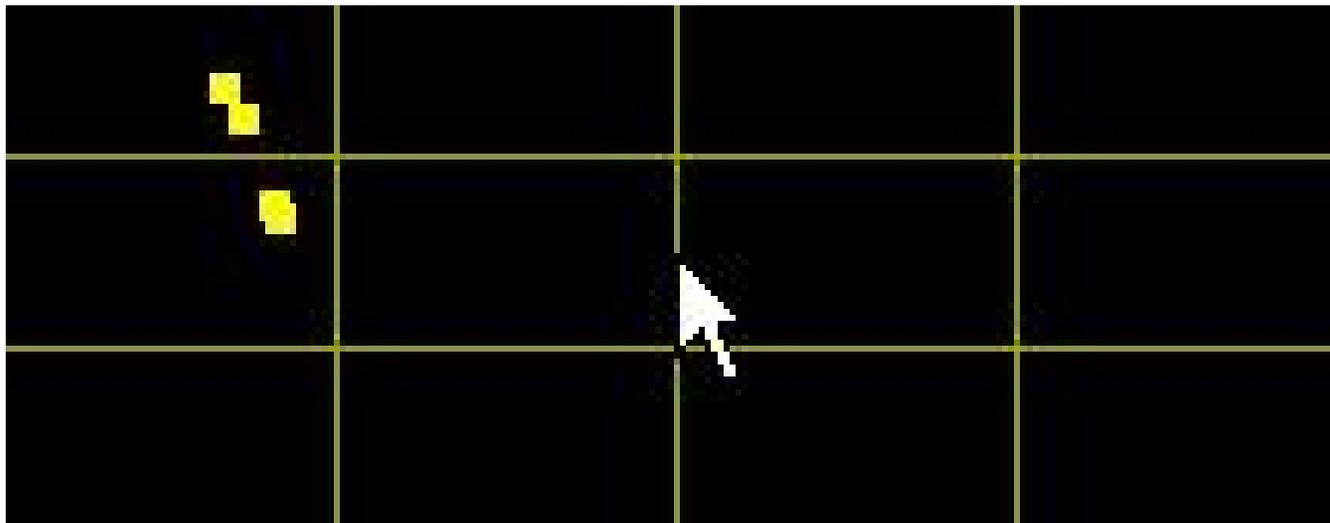
# Data Acquisition Software

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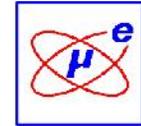


## □ Real-time visualization

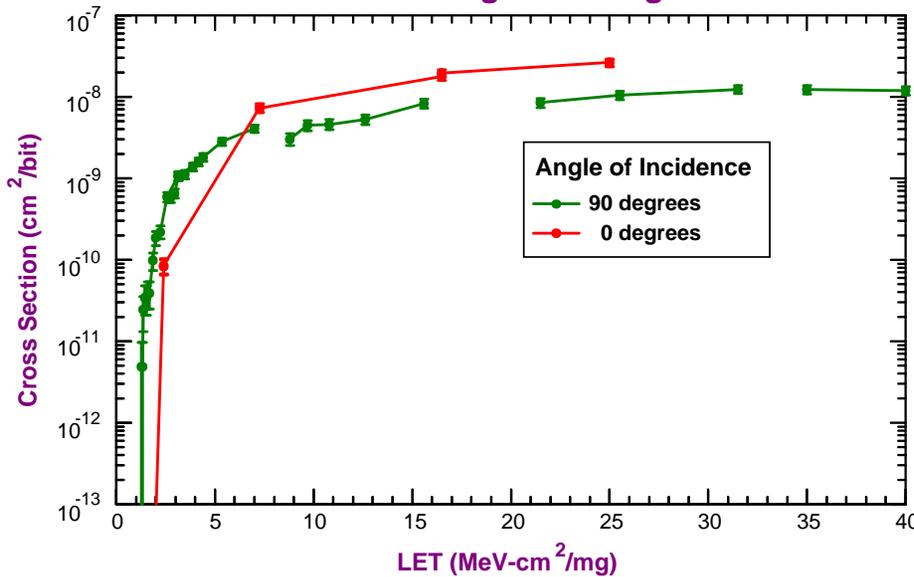
- Invaluable for locating - sweet spot in an acceptable amount of time
- Filtering options for error multiplicity
- Options for refresh rate
- Also critical for initial location & calibration of the Milli-Beam



# Bulk and 0.7 $\mu\text{m}$ SOI – 90° and 0° Results



Bulk 90-deg and 0-deg Data



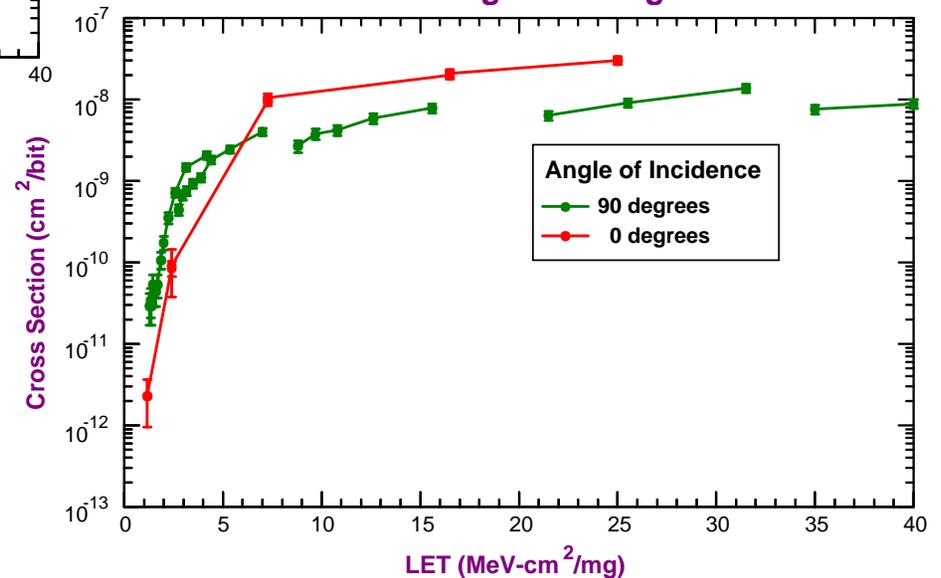
## □ Bulk Results

- Collection length appears to be longer for 90° beam
- Saturated cross section smaller for 90° beam
- Implies very shallow collection depths

## □ SOI Results

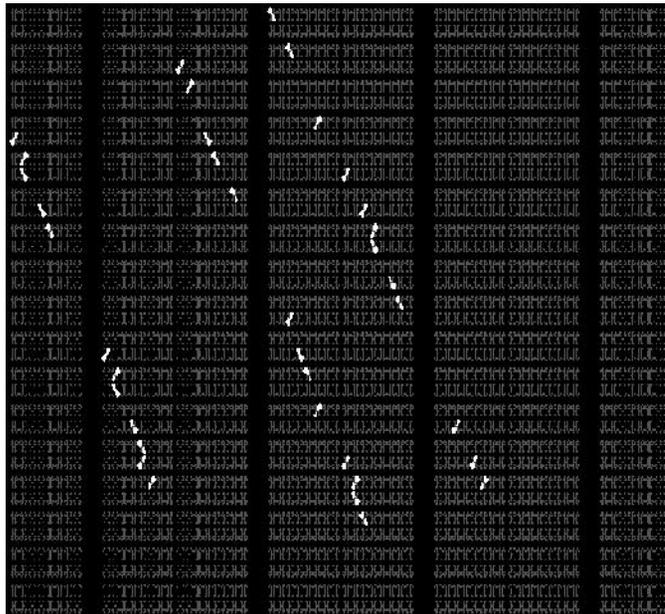
- No significant reduction in saturated cross section
- No significant increase in threshold LET
- Also implies very shallow collection depths

SOI 90-deg and 0-deg Data



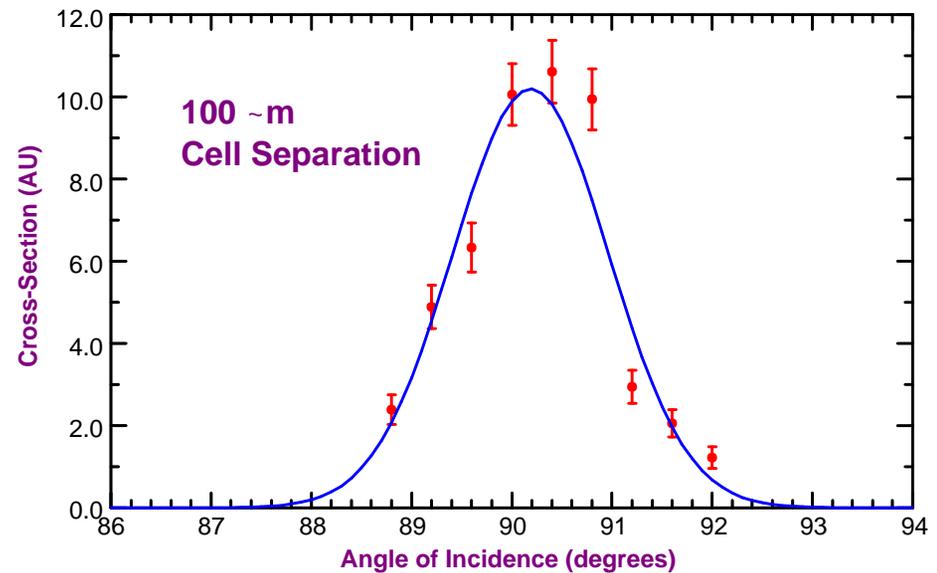


# Required Critical Node Separations



- ❑ 90° incident heavy ions
- ❑ Ne ion in the LBL 16A MeV cocktail
- ❑ Range ~240  $\mu\text{m}$

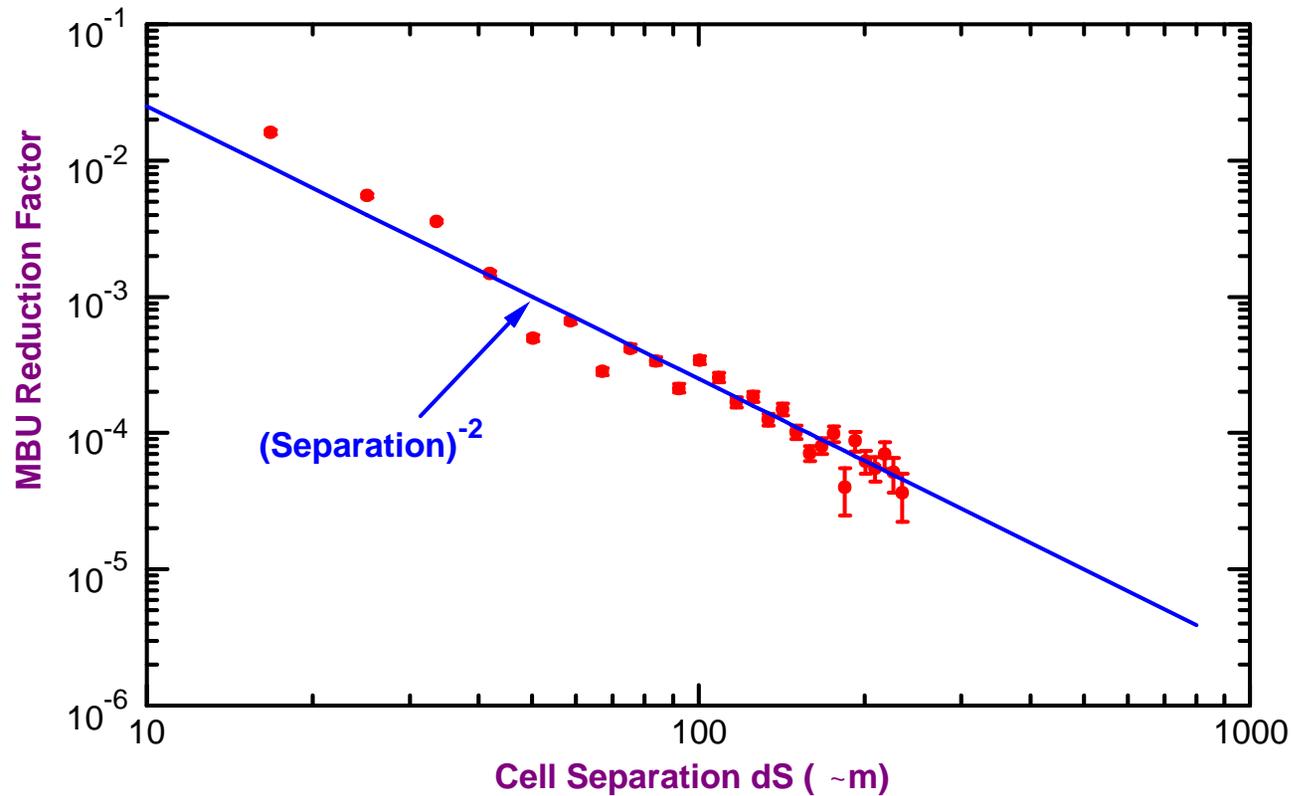
- ❑ Step angle of incidence
- ❑ Measure separation of each MBU
- ❑ Least-squares fit provides MBU integration over solid angle
- ❑ Compare the MBU integrated error rates to  $2f \cdot \text{SEU rate}$





# Error Rate Estimate for Redundant Circuit

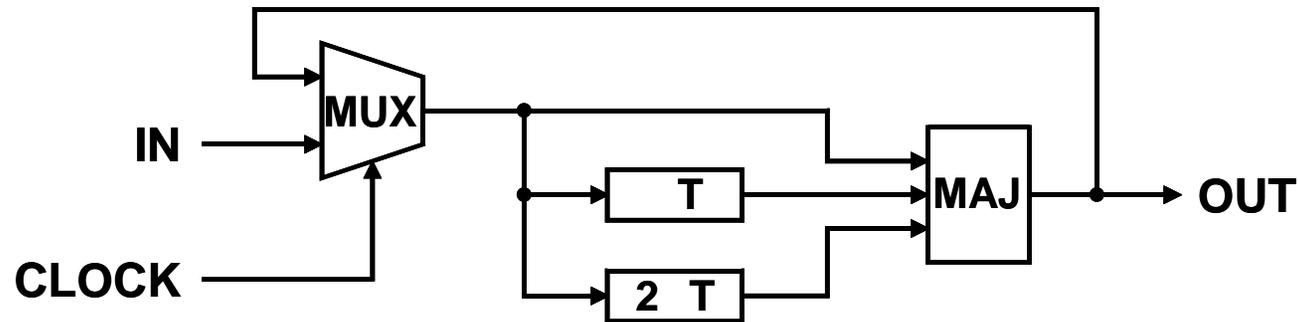
- ❑ Error rate for no redundancy =  $R_0$
- ❑ Reduction factor at cell separation =  $F(ds)$
- ❑ Hardened design error rate then =  $R_0 \cdot F(ds)$



# Temporal Latch Solution



U.S. Patent No. 6,127,864



- ❑ Triple spatial redundancy achieved through temporal sampling
- ❑ Inherently immune to transients of width  $< UT$  on any node
- ❑ Can be made immune to multiple node strikes of any multiplicity
  - Make  $UT > \text{transient width} + \text{loop delay}$
  - Lay out so  $UT$ ,  $2UT$ , and MUX/MAJ are in separate rows
- ❑ Well de-biasing problems when  $UT$  and MUX/MAJ shared an n-well
  - New  $UT$  design solved this (to be patented from our SASIC SBIR)
  - New design proven non-upsetable in recent AFRL heavy-ion tests

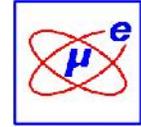
# Tradeoffs Between DICE and Temporal

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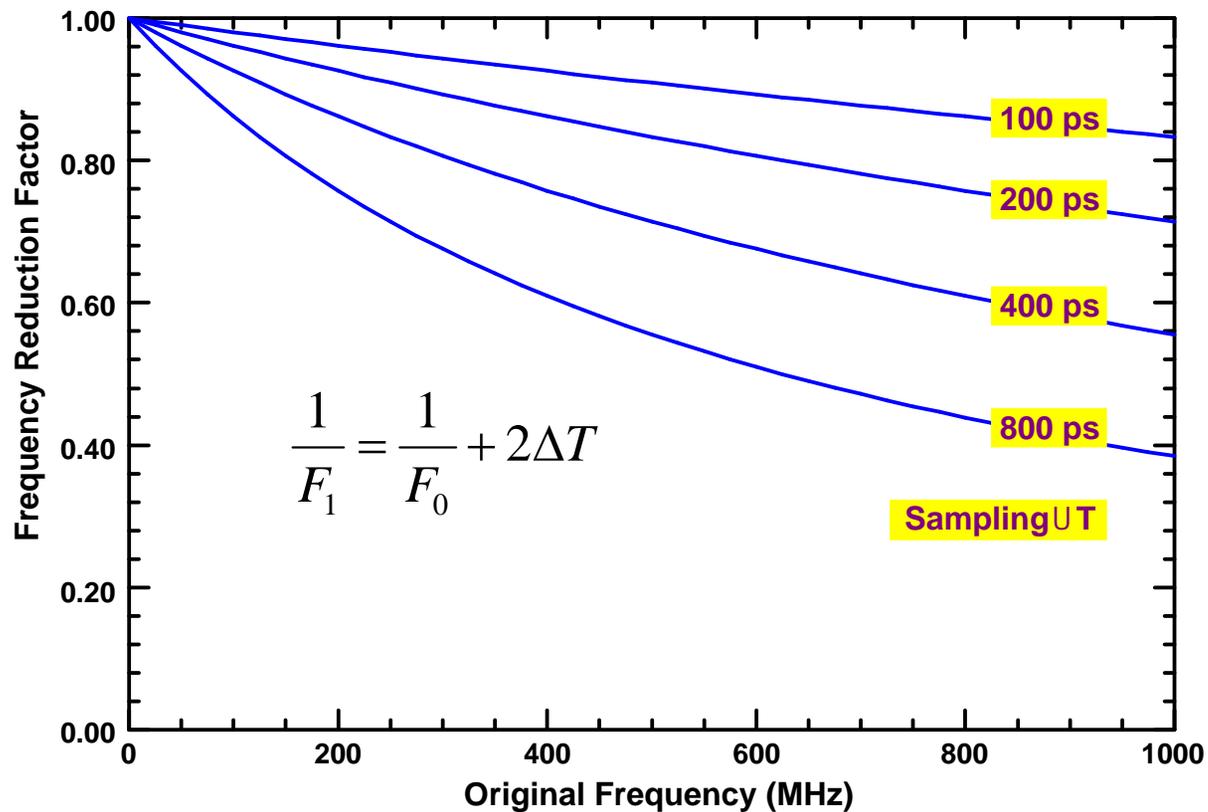


- Full up Set/Reset DICE transparent latch**
    - 28 transistors + 5 UT delay elements
  
  - Full up Set/Reset Temporal transparent latch**
    - 28 transistors + 3 UT delay elements
  
  - Full up Set/Reset DICE DFF**
    - 48 transistors + 5 UT delay elements
  
  - Full up Set/Reset Temporal DFF**
    - 52 transistors + 6 UT delay elements
  
  - Same speed loss for each (2UT setup/hold time increase)**
  
  - Temporal TLAT and DFFs immune to multiple node strikes**
-

# Speed Tradeoffs for Various UT Values



- Formulate as a frequency reduction factor ( $F_1/F_0$ )
  - Will depend on original operating frequency  $F_0$
  - Assume a setup/hold increase time of  $2UT$



# Recent Relevant Micro-RDC Efforts

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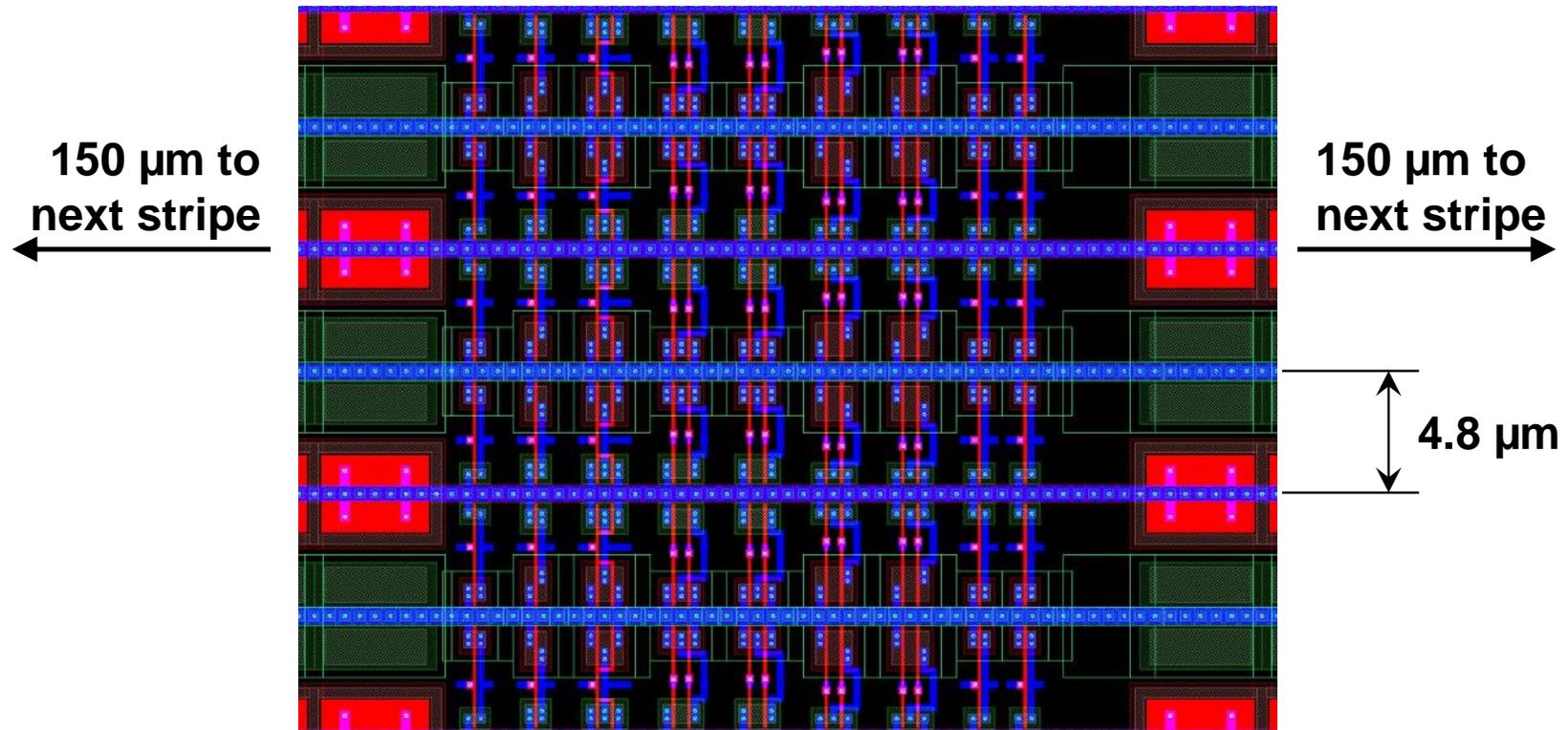


- ❑ **Extended our earlier DSET investigations**
  - Characterize, model, simulate DSET effects in emerging technologies
  - Upgrade and develop new test hardware and data analysis methods
  - Improve several earlier DSET test structures
  - Develop new DSET characterization structures and methods
  
- ❑ **Developed our heavy-ion Milli-Beam™ for use at the LBL cyclotron**
  - New hardware and software to raster scan complex ICs
  - Achieve spatial resolutions between 10 μm and 500 μm
  
- ❑ **Initial hardening investigations of a PLL**
  - Identified candidate designs
  - Performed coarse Milli-Beam scans



# Example Propagation Chain Layouts

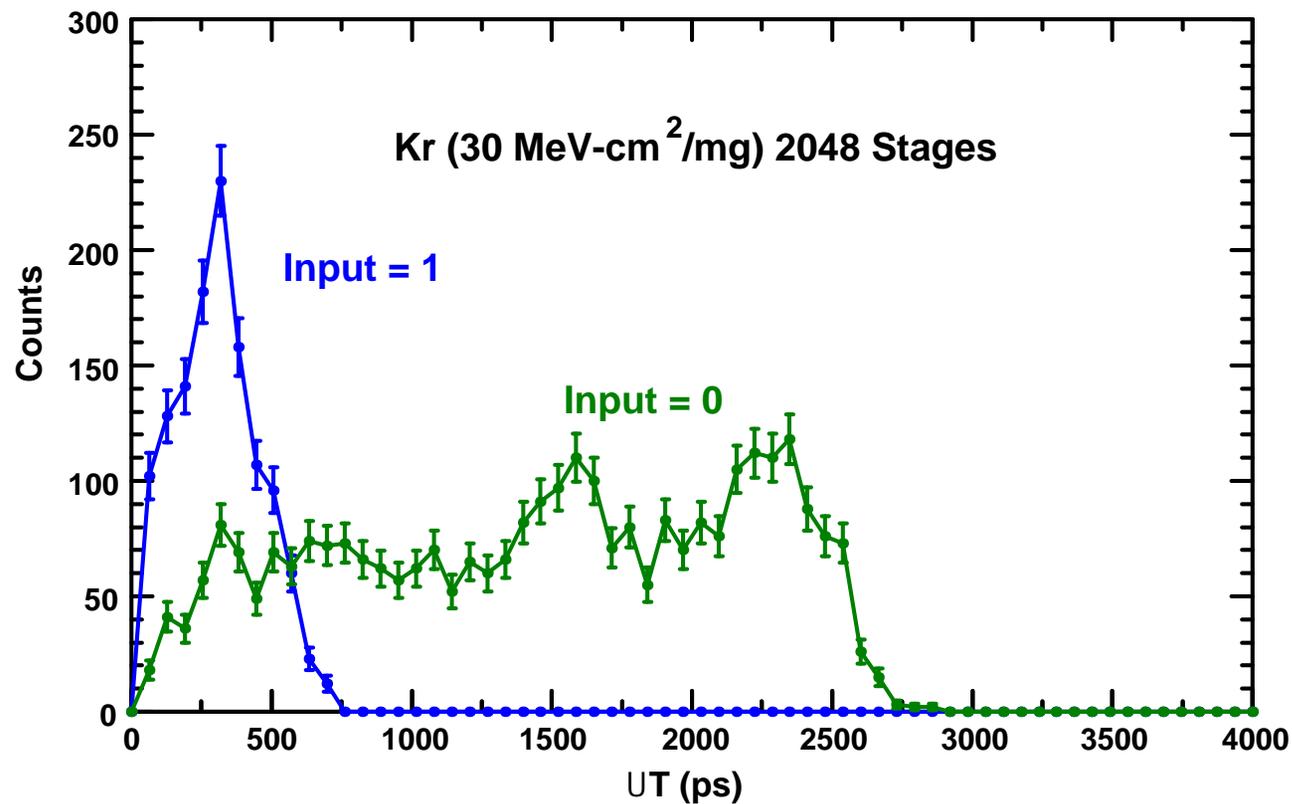
- ❑ Up-Down transient propagation
- ❑ 8 chains adjacent to one another
- ❑ Wide separations between vertical stripes (for Milli-Beam testing)



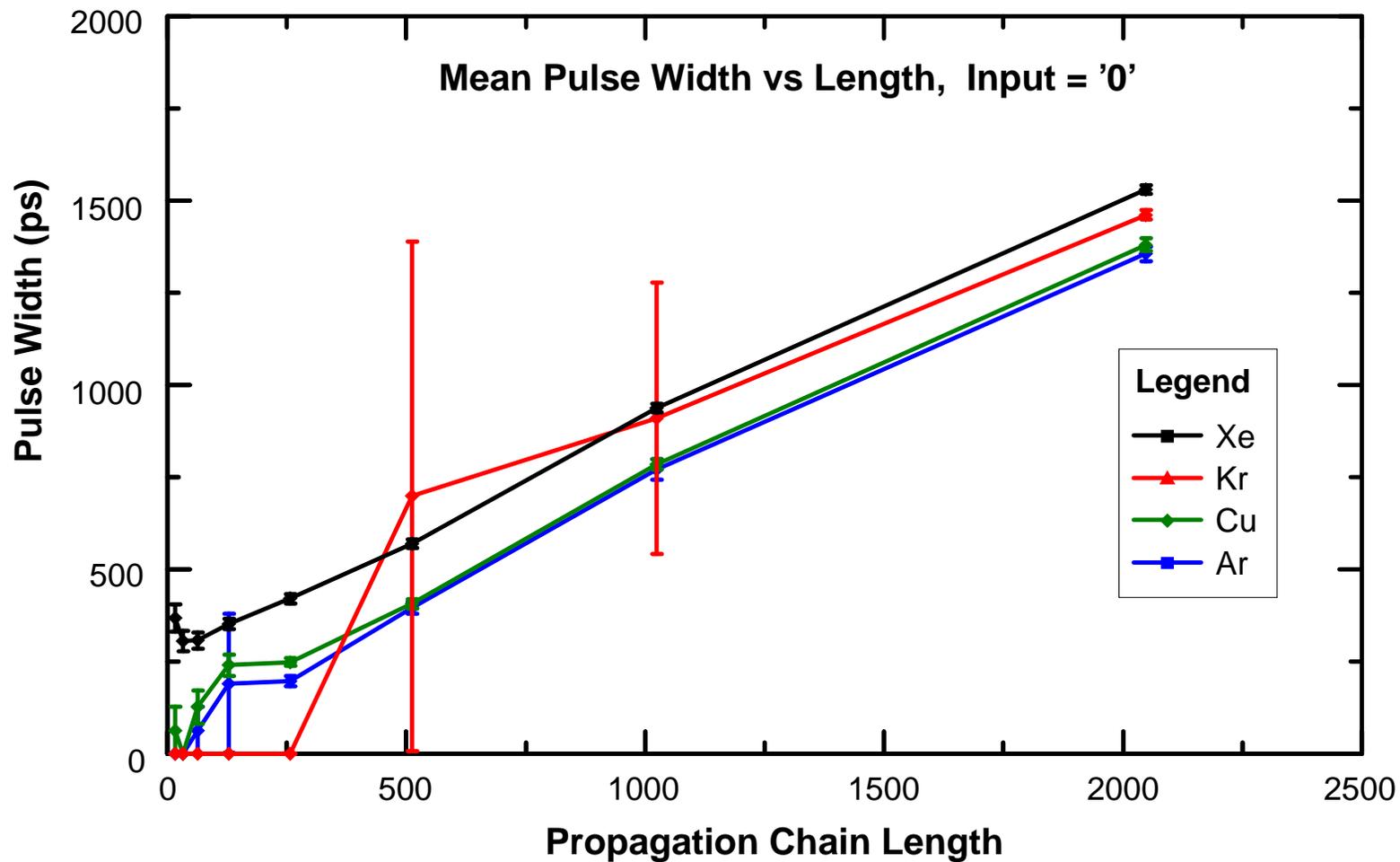
# Sample Differential Pulse Width Distributions



- ❑ Broadening effects clear for "0" state data
- ❑ Multi-Transistor modulation might be altering the "1" state data



# Mean Pulse Width vs. Length, Input='0', INV1



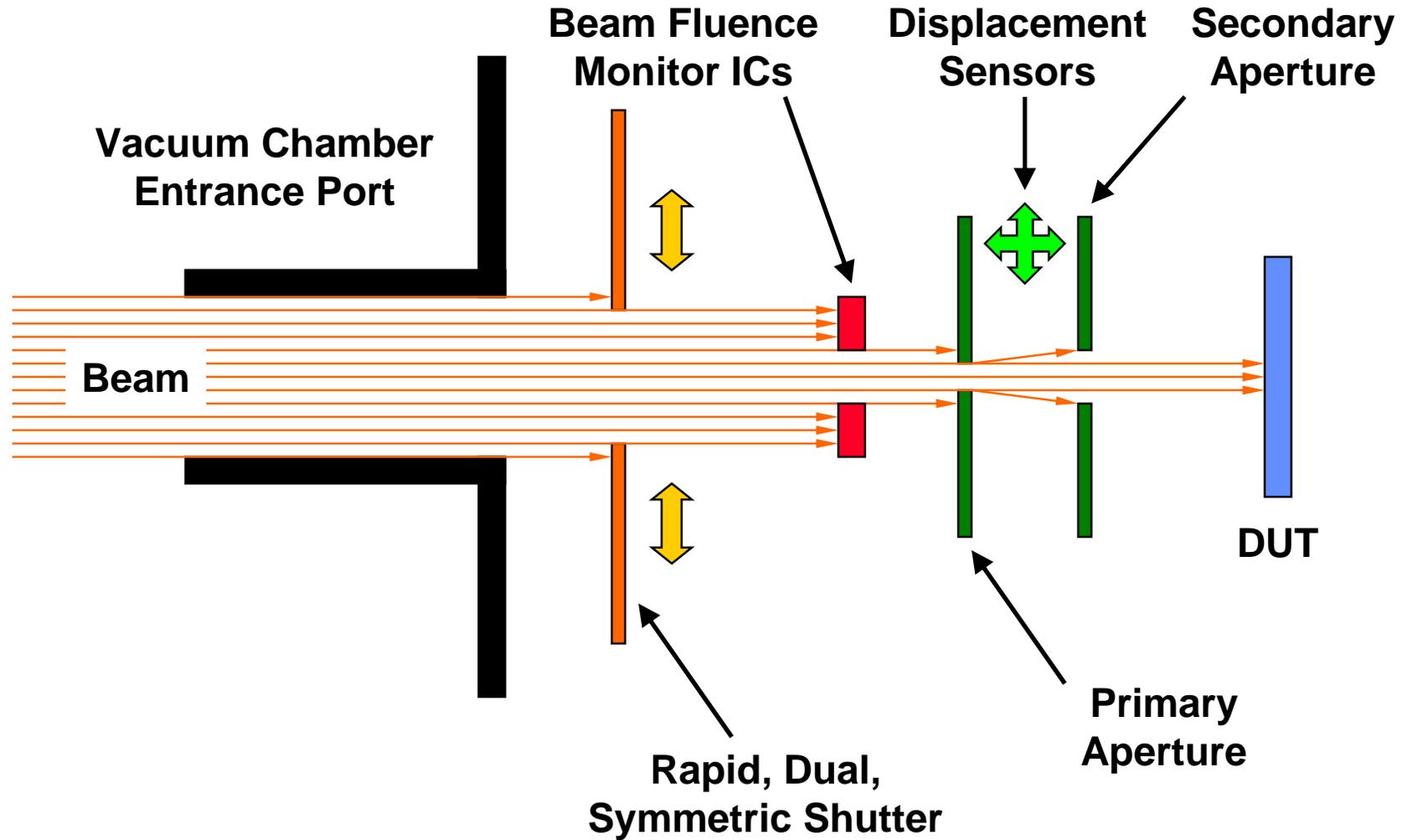
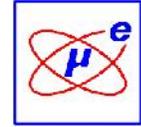
# Heavy-Ion Milli-Beam at the LBL Cyclotron

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- ❑ **Precise beam collimation for use at the LBL cyclotron**
    - New hardware and software to raster scan complex ICs
    - Achieve spatial resolutions between 5 μm and 500 μm
  - ❑ **Hardware**
    - Primary square aperture (2-orthogonal slits) stepped <1 μm precision
    - Secondary scattering cleanup aperture controlled from second stage
    - Displacement sensors provide error feedback signal for corrections
  - ❑ **Software**
    - Computes coordinate transformations, sets beam position, controls run
    - Provides FPGA test board with positions for inclusion in error message
  - ❑ **Independent ICs for beam characterization and dosimetry**
    - Homogeneous RAM for location and intensity profile measurement
    - Specially designed beam monitor ICs placed upstream of apertures
    - At preset fluences: block the beam, stop data acquisition, step apertures, update FPGA test board with new position, resume data acquisition, unblock the beam
-

# Milli-Beam Schematic



# Numerous Physical Considerations

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- ❑ Displacement and rotation of DUT w.r.t. calibration SRAM
- ❑ SRAM Y-axis rotation w.r.t. Milli-Beam Y-actuator
- ❑ Non-orthogonally of Milli-Beam X and Y actuators
- ❑ Berkeley Stage Y-axis rotation w.r.t. Milli-Beam Y-actuator<sup>†</sup>
- ❑ Non-orthogonally of Berkeley X and Y actuators<sup>†</sup>
- ❑ Dimensional scaling of each actuator<sup>†</sup>

<sup>†</sup>Only if need to move Berkeley Stage to bring DUT into Milli-Beam Range

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## Final Form of the Transformation

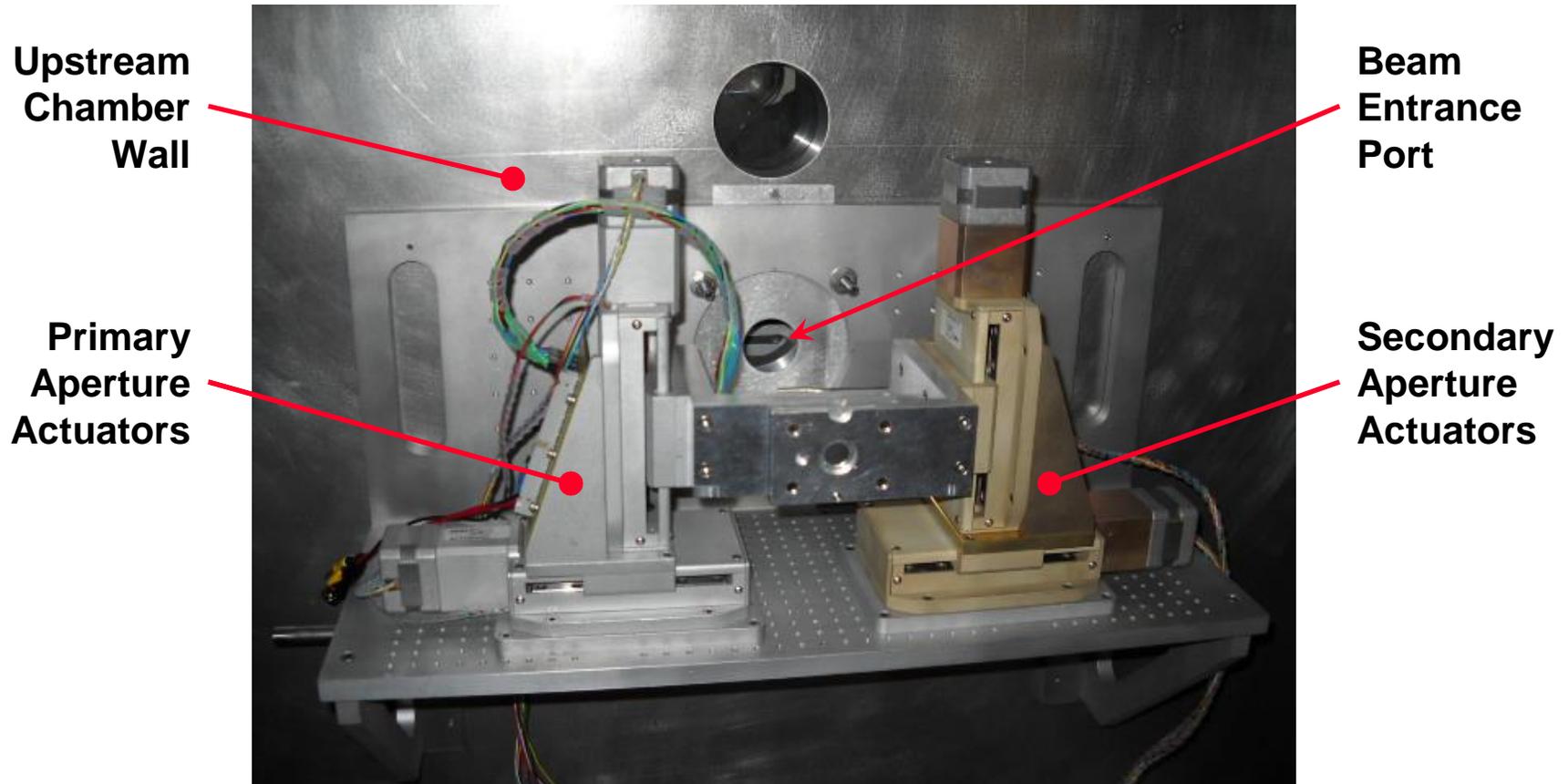
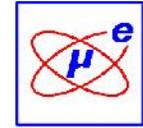
- Transformation to compute Milli-Beam raster scan movements

$$\begin{pmatrix} x_m \\ y_m \end{pmatrix} = \begin{matrix} O \\ \begin{bmatrix} \times & \times \\ \times & \times \end{bmatrix} \end{matrix} \cdot \begin{matrix} R^{-1} \\ \begin{bmatrix} \times & \times \\ \times & \times \end{bmatrix} \end{matrix} \cdot \left\{ \begin{matrix} R_D^{-1} \\ \begin{bmatrix} \times & \times \\ \times & \times \end{bmatrix} \end{matrix} \cdot \begin{pmatrix} x_{dut} \\ y_{dut} \end{pmatrix} + \begin{pmatrix} x_D \\ y_D \end{pmatrix} \right\}$$
  
$$\begin{pmatrix} x_D \\ y_D \end{pmatrix} = \begin{pmatrix} x_{D_o} \\ y_{D_o} \end{pmatrix} + \begin{matrix} R_{\mu} \\ \begin{bmatrix} \times & \times \\ \times & \times \end{bmatrix} \end{matrix} \cdot \begin{matrix} R_{\{ }^{-1} \\ \begin{bmatrix} \times & \times \\ \times & \times \end{bmatrix} \end{matrix} \cdot \begin{matrix} O_{\{ }^{-1} \\ \begin{bmatrix} \times & \times \\ \times & \times \end{bmatrix} \end{matrix} \cdot \begin{matrix} S_{\{ } \\ \begin{bmatrix} \times & \times \\ \times & \times \end{bmatrix} \end{matrix} \cdot \begin{pmatrix} ux_b \\ uy_b \end{pmatrix}$$

- $\mu$  → SRAM w.r.t. Milli-Beam;       $D$  → DUT w.r.t. SRAM  
 $\{$  → Berkeley w.r.t. Milli-Beam;       $b$  → Berkeley stage movement

- Inverse transformation used to compute DUT location, along with an estimate of the variance, for each Milli-Beam raster position

# Complete Assembly in Berkeley Chamber



# Primary Aperture Assembly

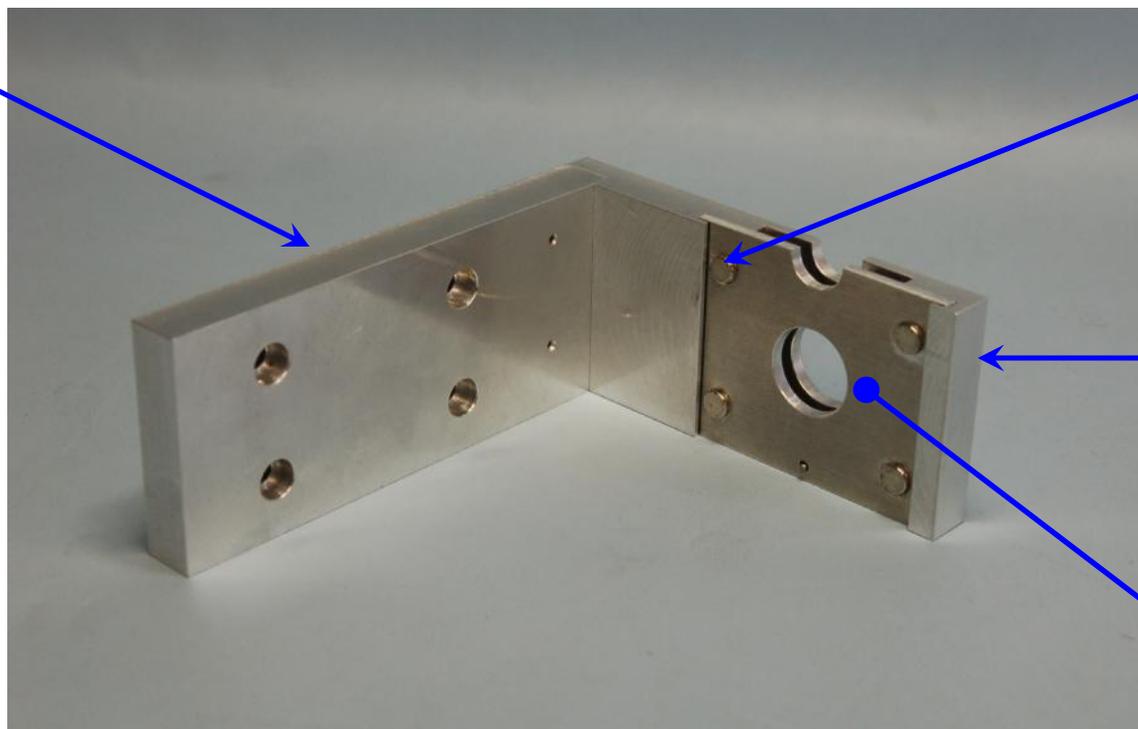
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# Aperture Mounting Assembly



**Bracket  
to Mount  
to Stage**



**Neodymium  
Magnets (4)**

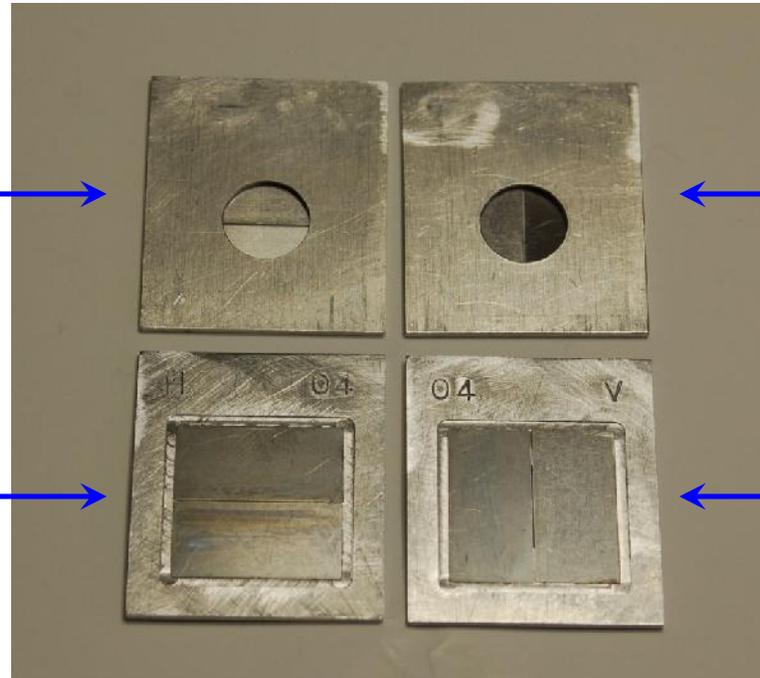
**Slit Holder**

**Pressure  
Plate**

# Aperture Construction



Outside View  
Horizontal Slit



Outside View  
Vertical Slit



Inside View  
Horizontal Slit



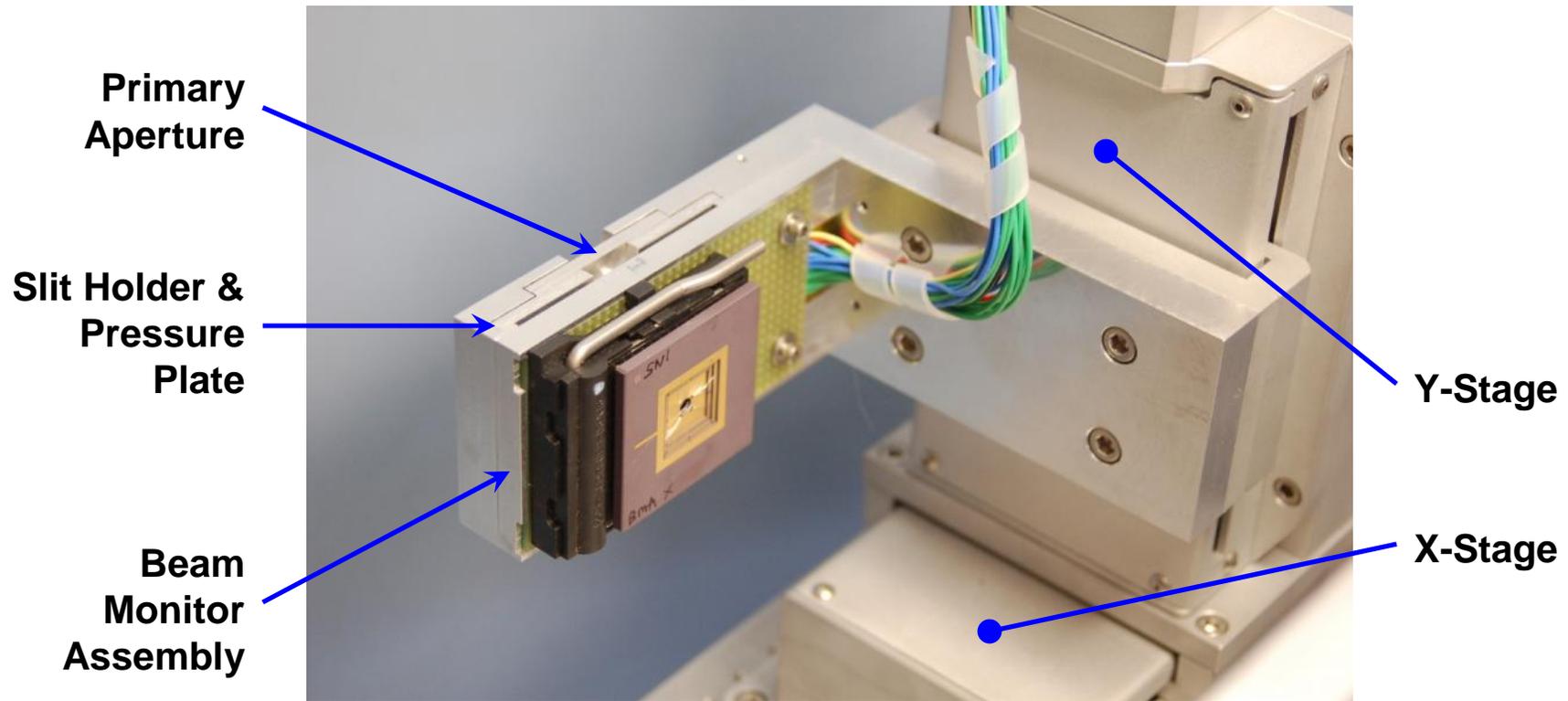
Inside View  
Vertical Slit



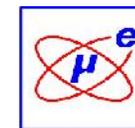
Fold to Assemble:



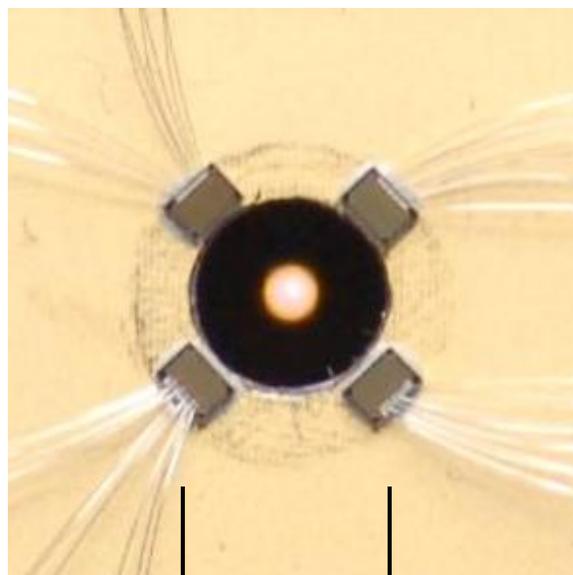
# Beam Monitor in Relation to Primary Aperture



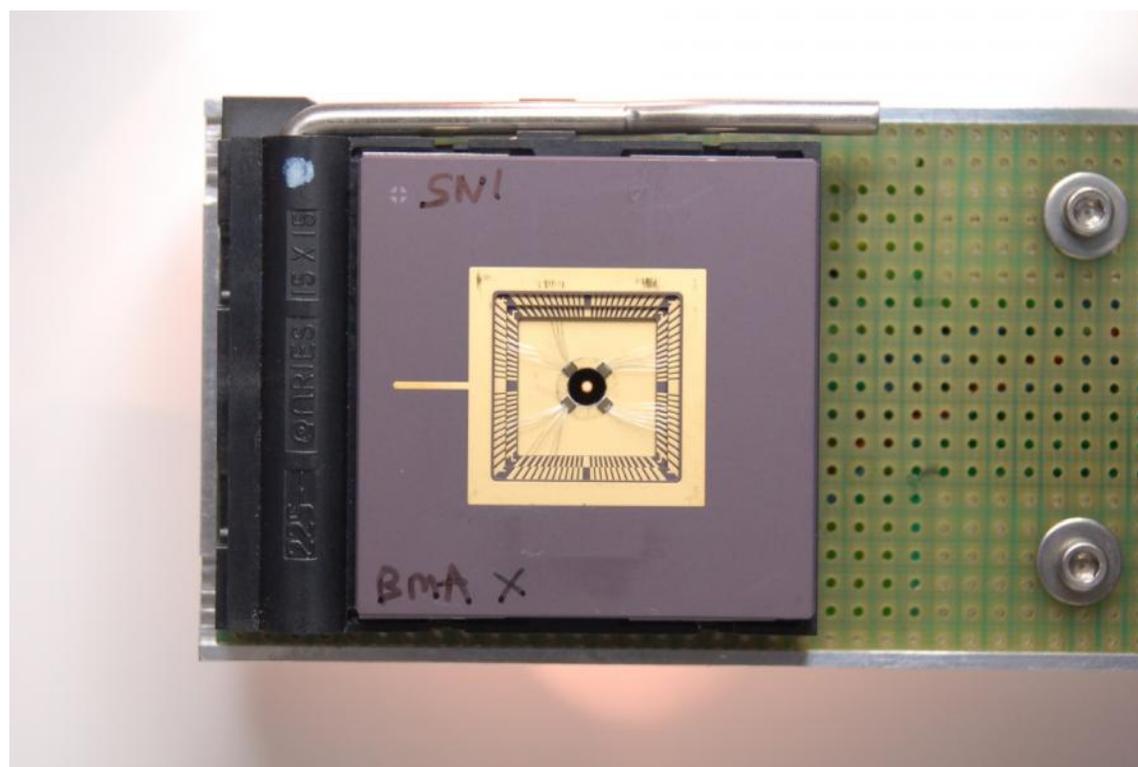
# View as Seen by the Heavy-Ion Beam



Zoomed View of Die



3.0 mm

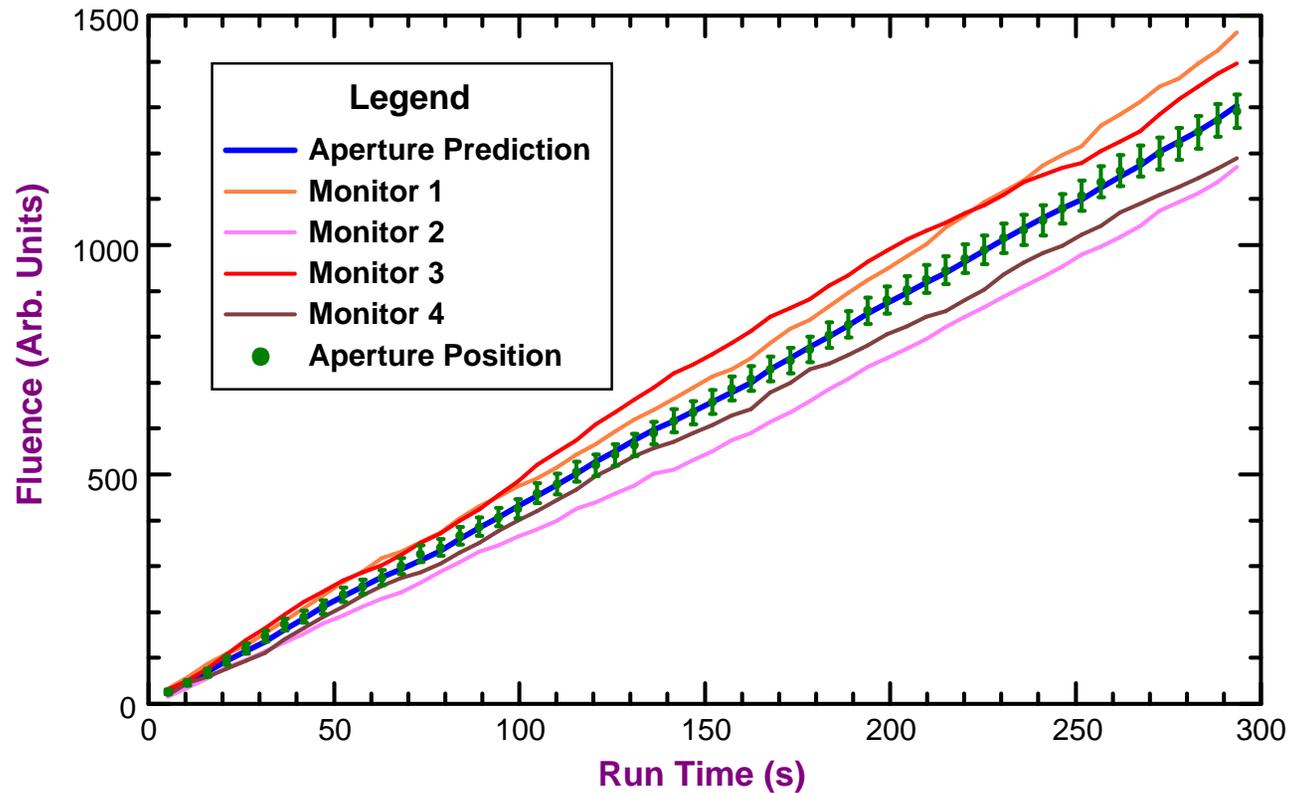


PGA, ZIF Socket, PERF Board

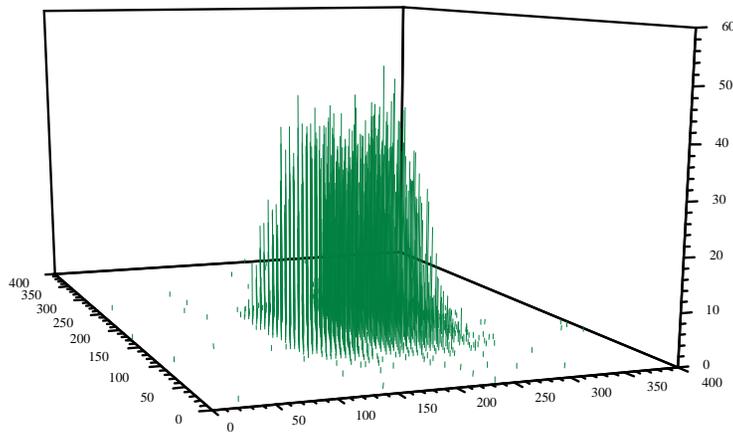
# Beam Fluence Monitor Accuracy



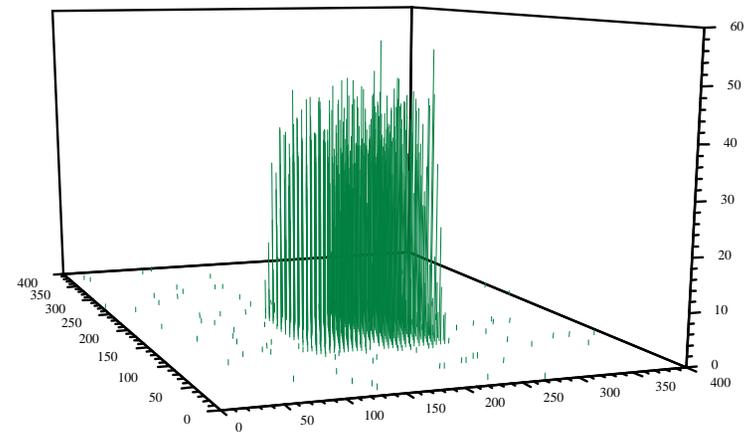
- Average the 4 monitor chip counts to predict beam flux at aperture



# Milli-Beam Intensity Profile Calibration

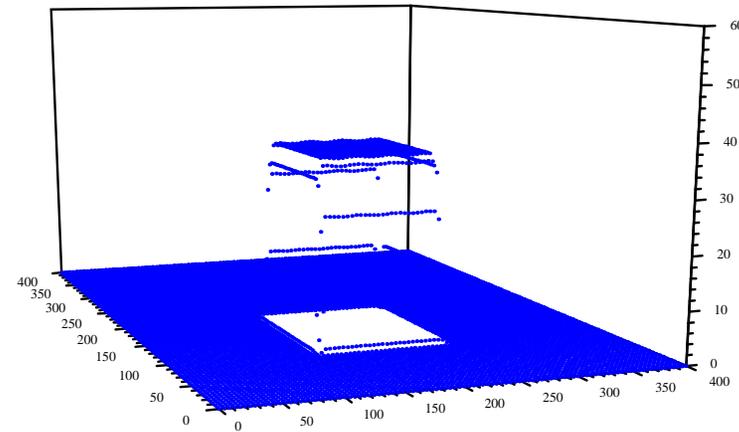
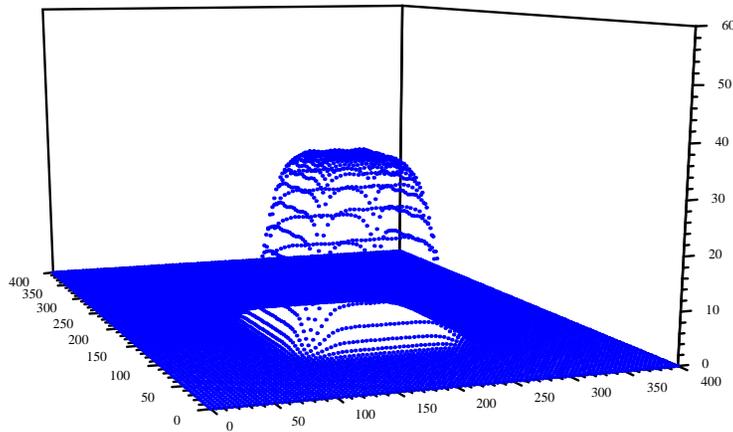


- ❑ 100  $\mu\text{m}$  square aperture
- ❑ Located 40 cm to SRAM
- ❑ Edge washout due to angular spread



- ❑ 100  $\mu\text{m}$  square aperture
- ❑ Located 5 cm to SRAM
- ❑ Sharper edge definition

# LSQ Fits to the Intensity Profile Function



- ❑ 2-d Convolution of a Gaussian product  $z(x)z(y)$  with an x-y-z box
- ❑ Center, width, length of aperture determined to  $< 1 \mu\text{m}$  accuracy
- ❑ Gaussian  $\dagger_x$  and  $\dagger_y$  determined to  $< 0.1 \mu\text{m}$  accuracy
- ❑  $\dagger$  values consistent with distance times tangent of  $0.0025^\circ$
- ❑  $\dagger$  at 5 cm distance measured to be  $\sim 2 \mu\text{m}$  in x and y directions

# Beam Fluence Monitor

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## □ Four special ICs

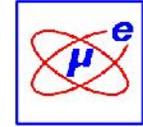
- Mounted just upstream of the Milli-Beam Primary Aperture
- Incorporates 8 chains of 1024 set-reset-flip-flops (RSFF)
- Electrically selectable cross section
  - Min = 1024 x 4 chips = 4,196 RSFF cells
  - Max = 8192 x 4 chips = 32,768 RSFF cells
- Extremely small dead time (~0.02% for  $10^7$  ions/(cm<sup>2</sup>isec))

## □ Calibrated to an accuracy of better than 1%

- Independent of the Berkeley dosimetry system
- Aperture of know size (as measured on a 90 nm SRAM)
- Particle detector counts individual heavy-ions through aperture
- Beam monitor IC events measured as a function of LET

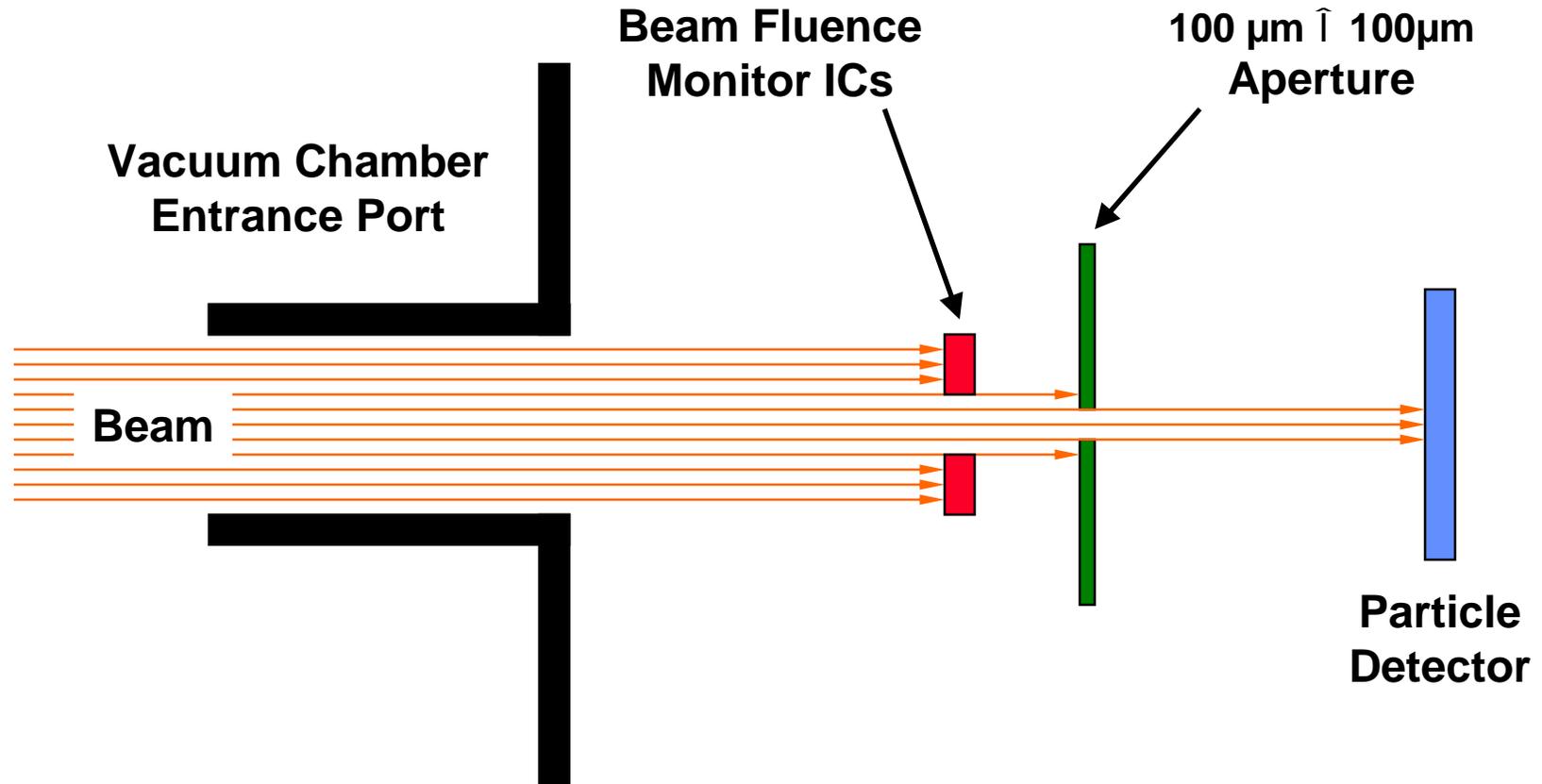
# Recent Beam Monitor Calibration Data

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- ❑ **10 ions available in the 10 MeV/nucleon cocktail**
  - **System cross-section calibrated from 0.89 to 58.8 MeV-cm<sup>2</sup>/mg**
  
- ❑ **Count events in each of the 4 beam monitor chips**
  - **Subject only to Poisson statistical uncertainties**
  
- ❑ **Collimate beam with known size aperture ( $\sim 100 \mu\text{m} \hat{\uparrow} \sim 100\mu\text{m}$ )**
  - **Measure precisely using our calibration RAM**
  
- ❑ **Use partially depleted Silicon particle detector to measure fluence**
  - **Count each and every heavy-ion passing through the aperture**
  
- ❑ **Determine cross-section as usual**
  - $\dagger = (\text{Number of Events}) / \text{Fluence}$

# Beam Monitor Calibration Schematic



# Calibration Equations



- Aperture height  $H$  and width  $W$  determine area  $A$ :

$$A = H \times W$$

- Particle detector counts  $N_{pd}$  then determine fluence  $F$ :

$$F = N_{pd} / A$$

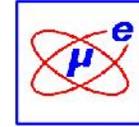
- Total beam monitor counts  $N_{bm}$  determine cross section " $\dagger$ ":

$$\dagger = N_{bm} / F$$

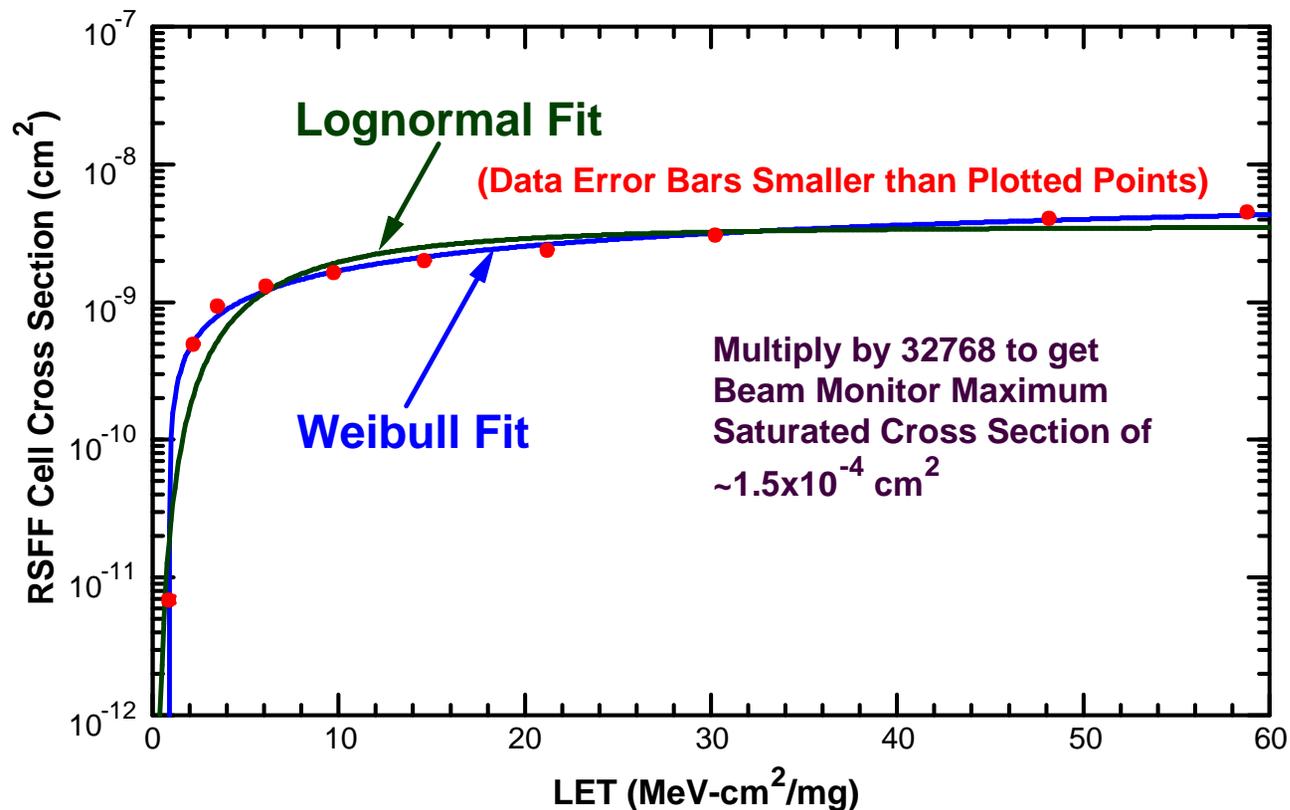
- Given the uncertainties  $dH$ ,  $dW$ ,  $dN_{pd} = (N_{pd})^{1/2}$ , and  $dN_{bm} = (N_{bm})^{1/2}$

$$\frac{d\dagger}{\dagger} = \sqrt{\frac{1}{N_{bm}} + \frac{1}{N_{pd}} + \left(\frac{dH}{H}\right)^2 + \left(\frac{dW}{W}\right)^2}$$

# Final Beam Monitor Cross Section



- ❑ System saturated cross section  $\sim 1.5 \times 10^{-4} \text{ cm}^2$
- ❑ 1500 counts/s at a modest Milli-Beam flux of  $1 \times 10^7 \text{ cm}^{-2} \text{ s}^{-1}$
- ❑ Achieves 1% accuracy in  $\sim 7$  seconds at each raster step



# How Good is the Berkeley Dosimetry?

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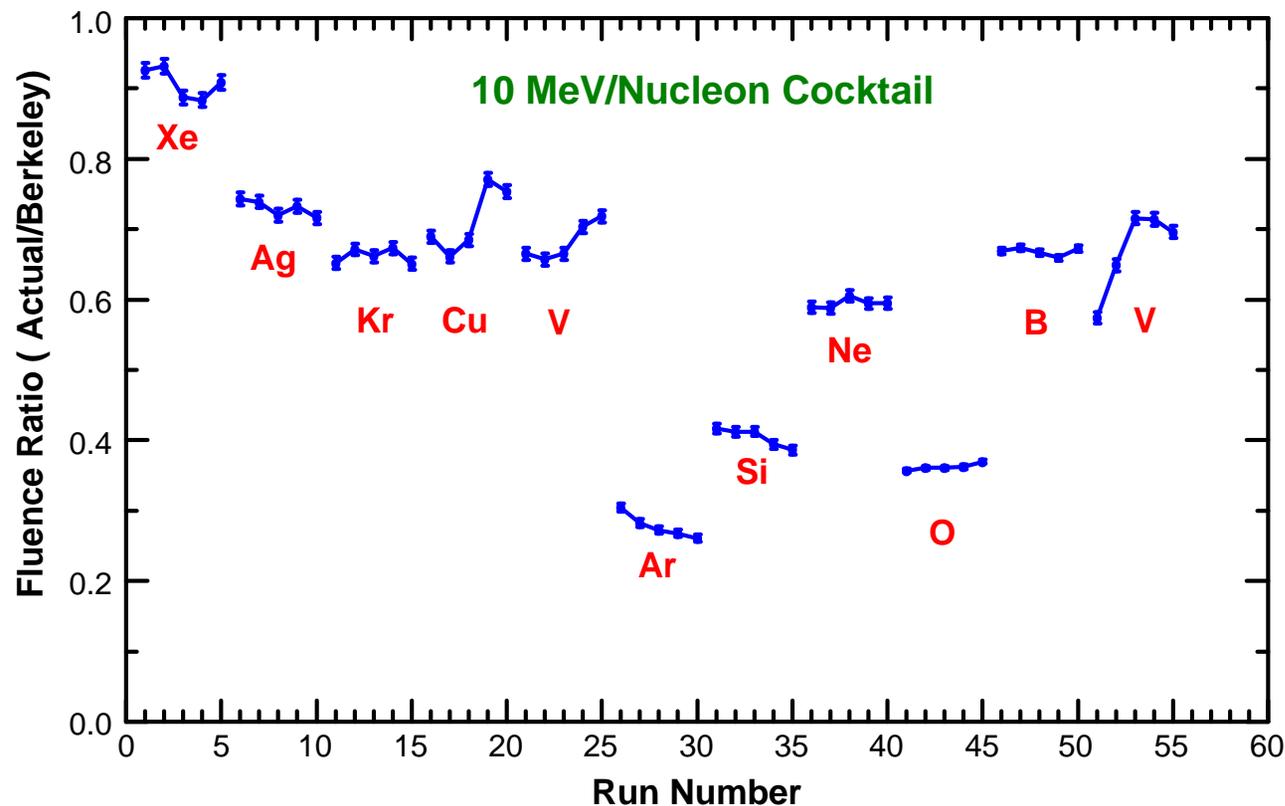


- ❑ They use 4 peripheral scintillators and a center scintillator
  - Calibration of the center to peripheral ratio periodically performed
  - Center scintillator removed to put beam on target
  - Peripheral scintillators then used to predict target flux
  
- ❑ This is particularly sensitive to changes in beam focus
  - If beam focus tighter, center flux higher but predicted to be lower
  - If beam defocuses, center flux lower, but predicted to be higher
  - Beam focus likely to change whenever switch ions
  
- ❑ Particle detector with aperture provides independent test
  - Beam monitor calibration made 5 runs for each ion
  - Each run stopped at  $1 \times 10^8$  ions/cm<sup>2</sup> fluence on Berkeley system
  - Can compare true fluence measurements with Berkeley values

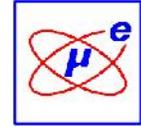
# Actual Measured Fluence vs Berkeley Values



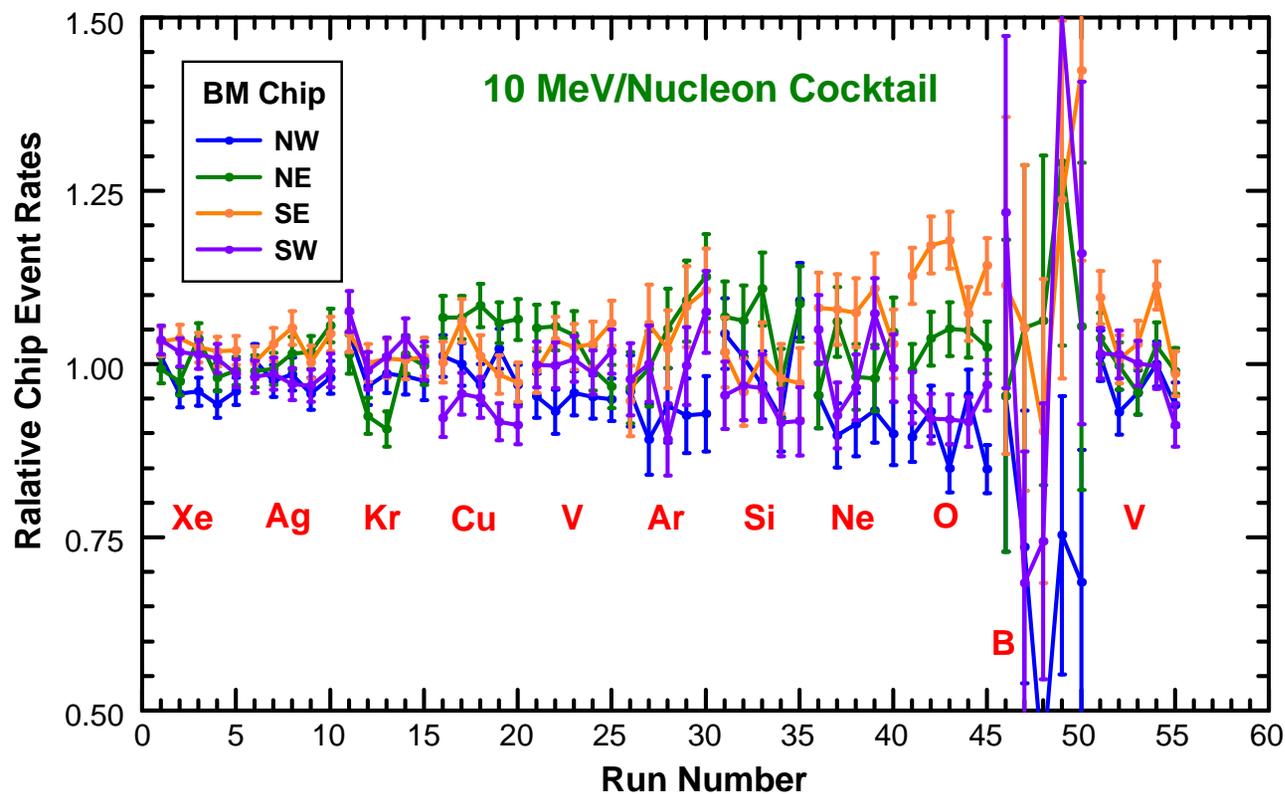
- ❑ ~10% variations when just repeat runs (common knowledge)
- ❑ Similar variations when return to an ion (should check further)
- ❑ >3x errors between species (this was a big surprise)



# Beam Focus Drifts Seen in Beam Monitor Chips



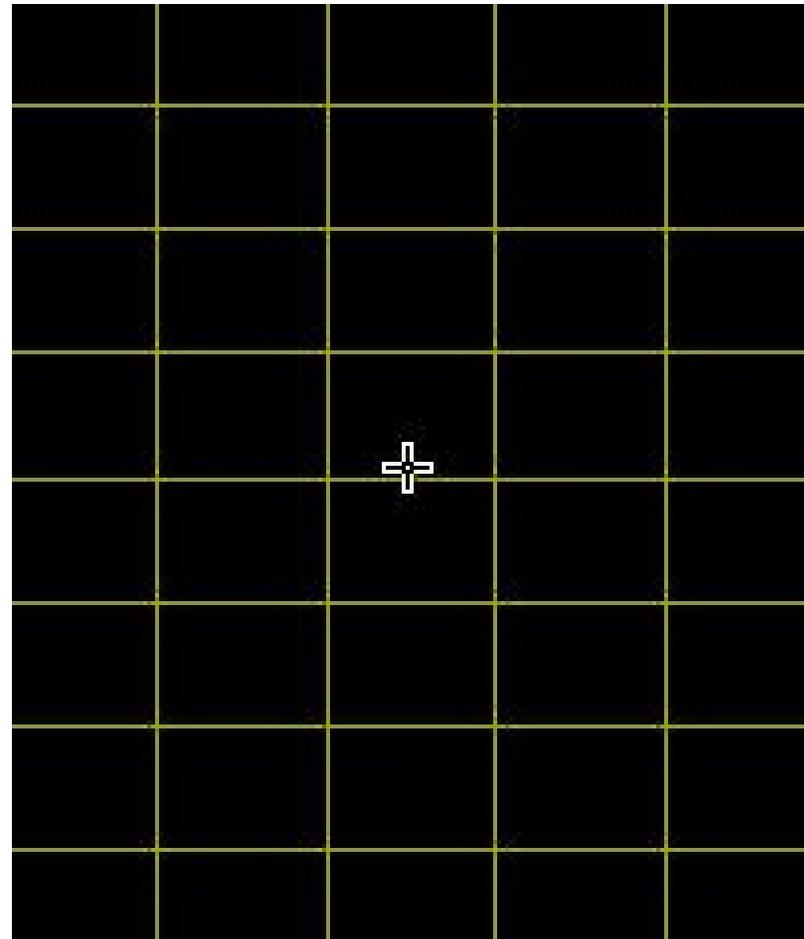
- ❑ Monitor each beam monitor chip independently
- ❑ Normalize counts so average of all data at each ion equals 1.0
- ❑ Beam profile variations evident over time and between species





# Example of a Raster Scan

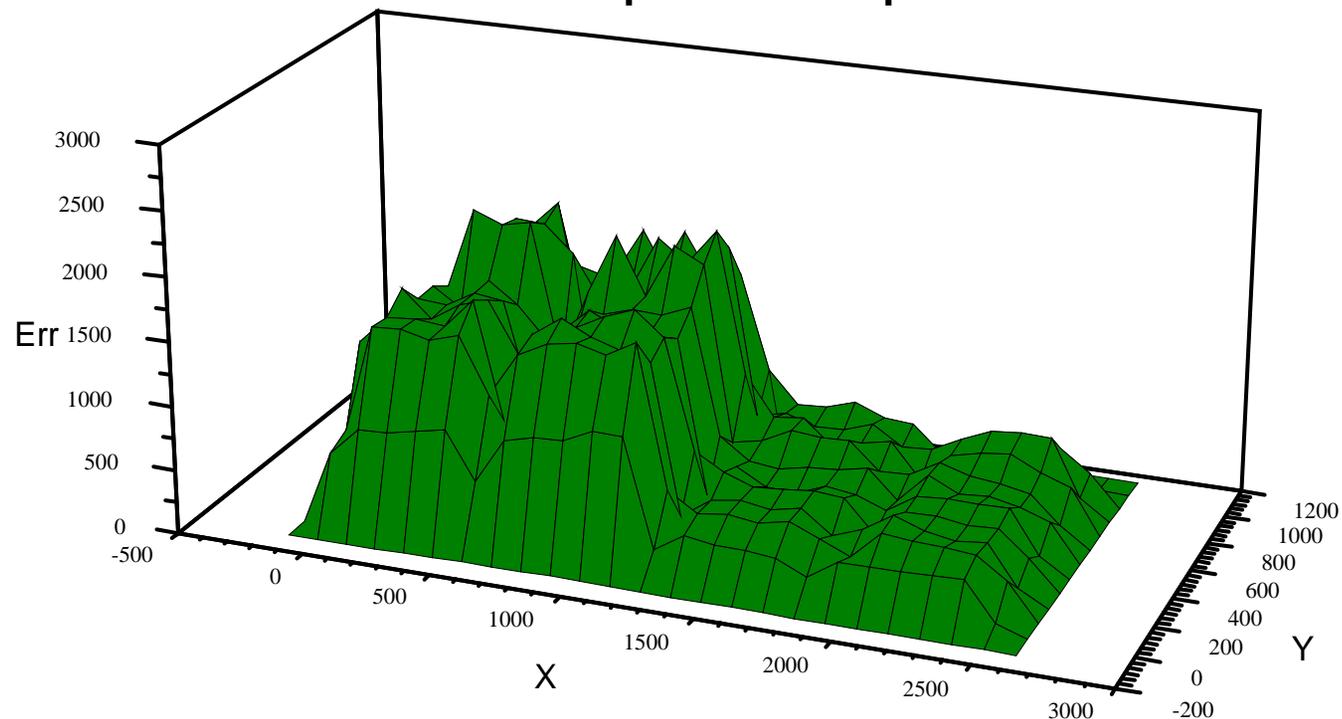
- ❑ **114  $\mu\text{m}$  x 101  $\mu\text{m}$  aperture**
  - As determined from LSQ fit
  
- ❑ **5 cm from SRAM**
  
- ❑  **$\gg 1 \times 10^6$  Ar ions/( $\text{cm}^2\text{-sec}$ )**
  - 10x normal beam intensity
  
- ❑ **Use aperture size for step size**
  - $U_x$  step = 114  $\mu\text{m}$
  - $U_y$  step = 101  $\mu\text{m}$
  
- ❑ **Scan in a serpentine pattern**
  - ~1.5 seconds/step
  - ~300 errors at each position



# SRAM Raster Scan Data Example



- Scan an SRAM on one of our earlier test chips
  - Two different cell designs – hardened layout on right half
  - Decode locations clearly seen in center of each array
  - Variations outside of statistical uncertainties due to beam fluctuations
  - Demonstrates the need to perform independent fluence monitoring



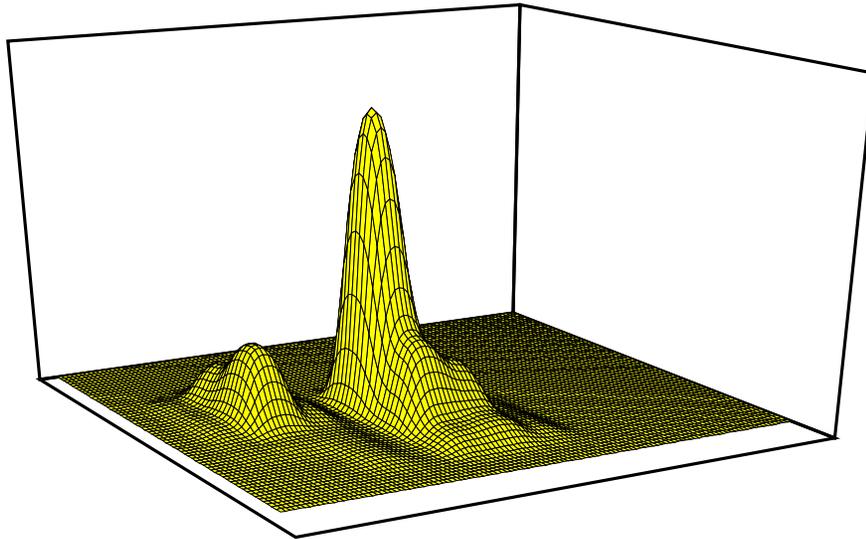
# Micro-RDC's PLL Hardening Efforts

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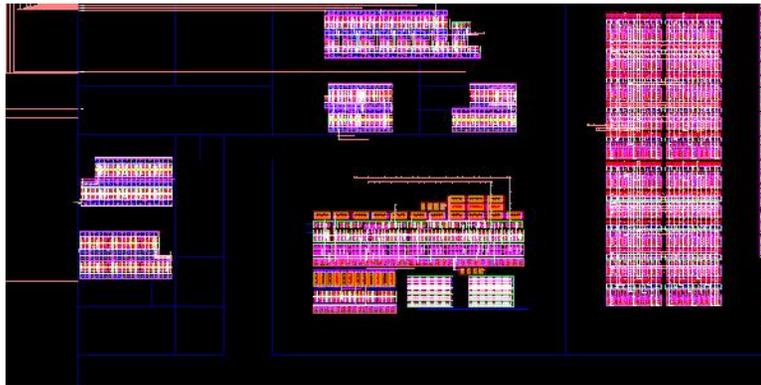


- ❑ **Designed a simple PLL, following commercial-like designs**
  - Under our AFRL Structured ASIC program
  - TID and SEL hardened with channel stops and edgeless NMOS
  - SEU and DSET susceptible
  
- ❑ **Performed coarse Milli-Beam scans**
  - Better approach than attempting to test standalone circuit components
  - Used  $100\ \mu\text{m} \hat{\ } 100\ \mu\text{m}$  aperture
  - Stepped over active layout in  $100\ \mu\text{m}$  X and Y steps
  - Monitored PLL loss of lock and time needed to regain lock
  - Correlate observed errors to specific circuits (CP, VCO, PSD, /N, xM)

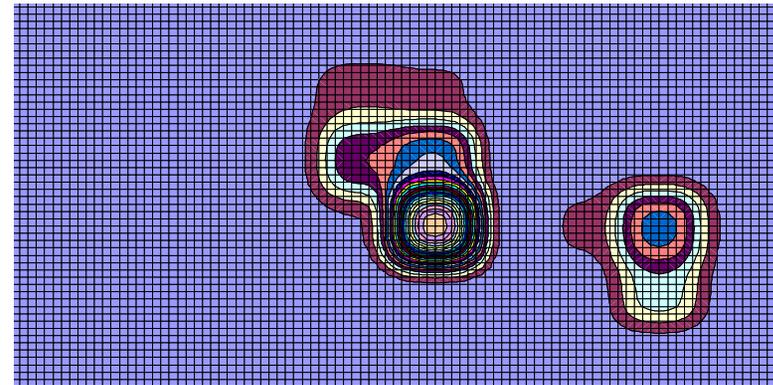
# Correlate PLL Errors to Physical Layout



View Direction for  
3D Surface Plot



Design Layout



Milli-Beam Error Contours

# Recommendation Summary

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- ❑ **Avoid use of spatial redundancy for SEU mitigation**
    - Node separations much too large for DICE and TMR
    - Use "by 1" block architecture with EDAC for SRAMs
  
  - ❑ **Use Temporal Sampling Latches for SEU and DSET mitigation**
    - Automatically achieves immunity to DSETs on any node
    - With new well de-biasing mitigation, automatically immune to multiple node strikes
  
  - ❑ **Tune the design to optimize hardness vs. speed vs. area**
    - Not all latches need the same UT filtering delay
    - Not all combinatorial gates generate the same sized transients
  
  - ❑ **Keep hardening implementation transparent to designer**
    - Reflect the RHBD consequences within the synthesis library
    - Require no HDL modifications to use the library
-